



Development and Certification of NIST Standard Reference Materials for Powder Diffraction

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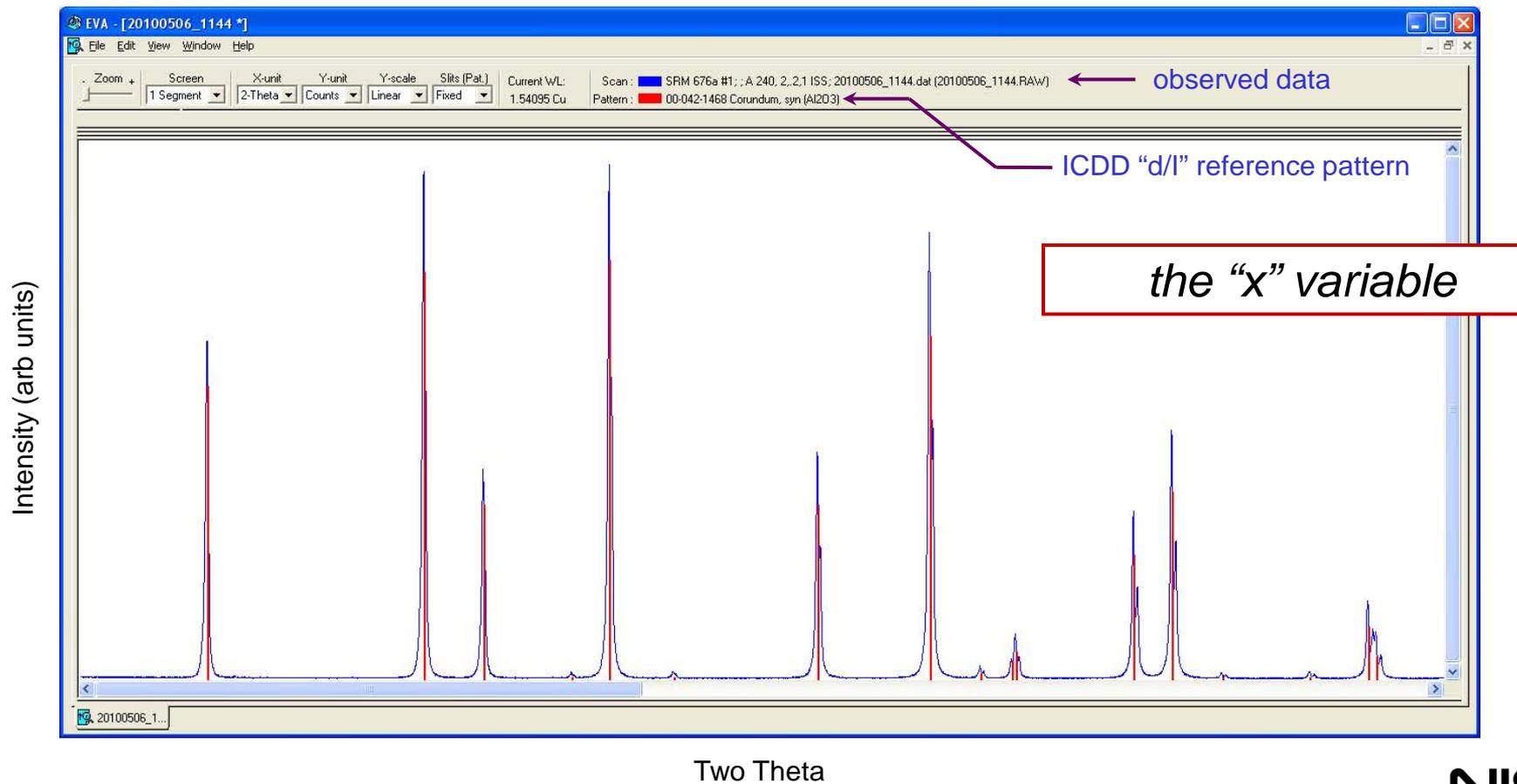
Robert W. Cheary

Richard D. Deslattes



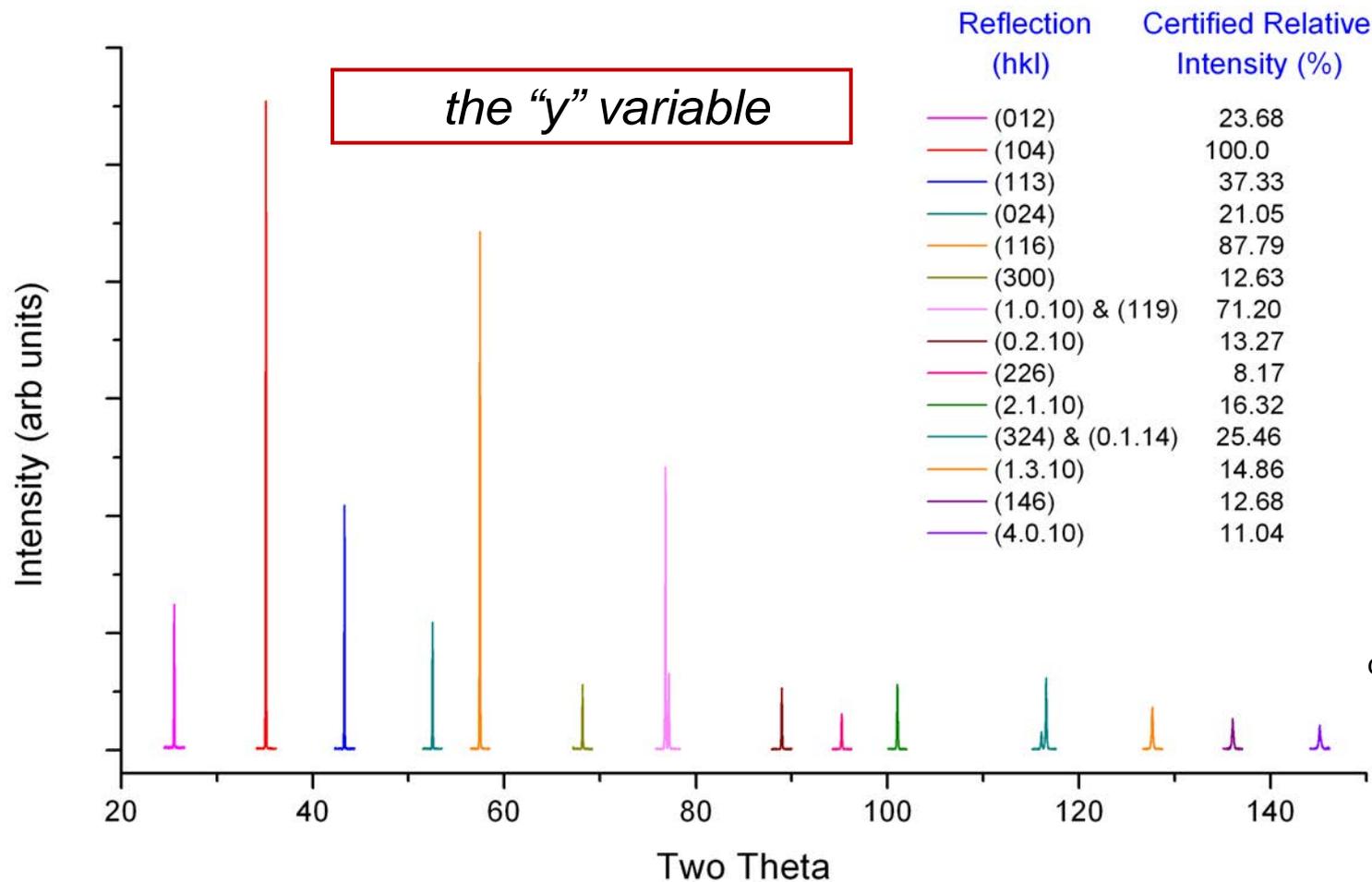
Calibration of Diffraction Line Position

*Qualitative phase analyses:
Improved performance of search/match algorithms*



Calibration for Instrument Response

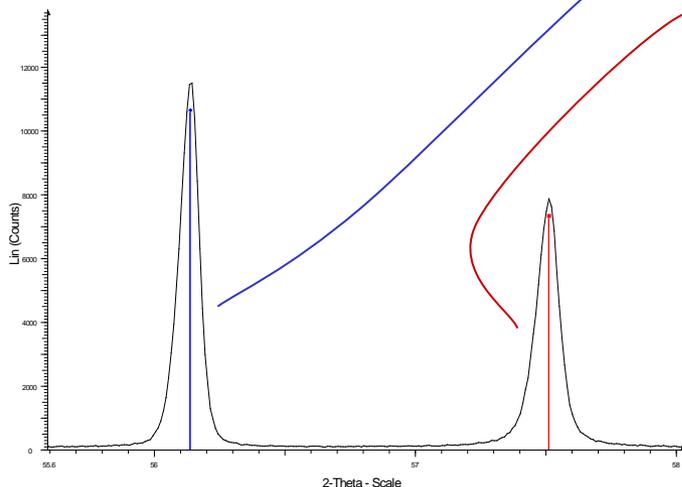
SRM 1976b: Suitable laboratory diffractometers using conventional data analysis methods



Sintered Al₂O₃ discs of SRM 1976b

Quantitative Phase Analyses

*SRM 676a, alumina powder,
certified with respect to absolute phase purity*



$$\frac{I_{\alpha}}{I_s} \left(\frac{I_{js}^{rel}}{I_{i\alpha}^{rel}} \right) RIR_{\alpha,s} = \frac{X_{\alpha}}{X_s}$$

**Reference Intensity Ratio, RIR,
(Internal Standard) Method**

I/I_c, the **RIR** of a given phase
relative to Al₂O₃ (corundum),
Parameter included in ICDD database

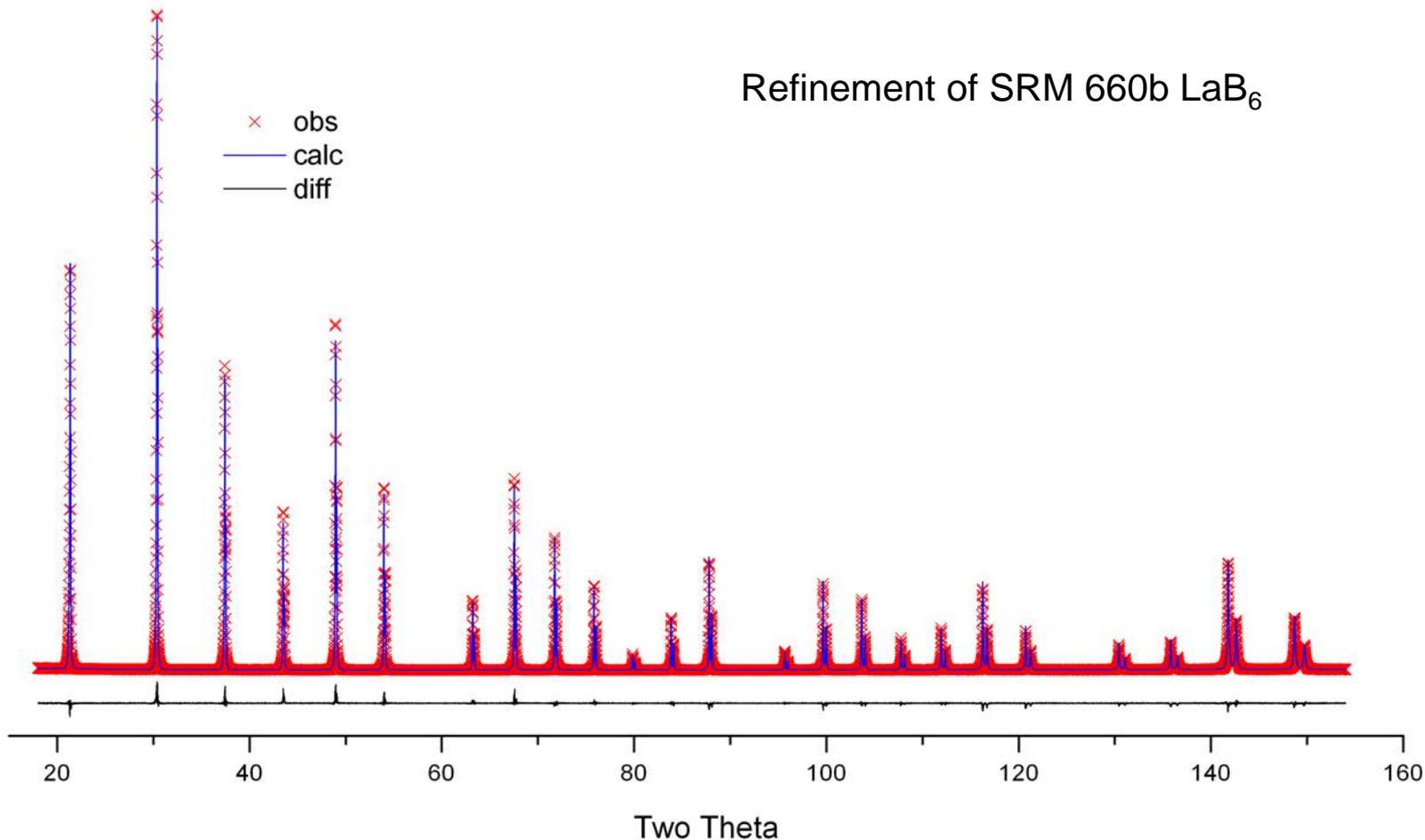
Boundary of any crystalline solid will include an amorphous component
Ultimate measurement issue: Crystalline phase purity



Rietveld Analysis of Powder Diffraction Data

Rigorous modeling of all aspects of the diffraction experiment for crystal structure analysis

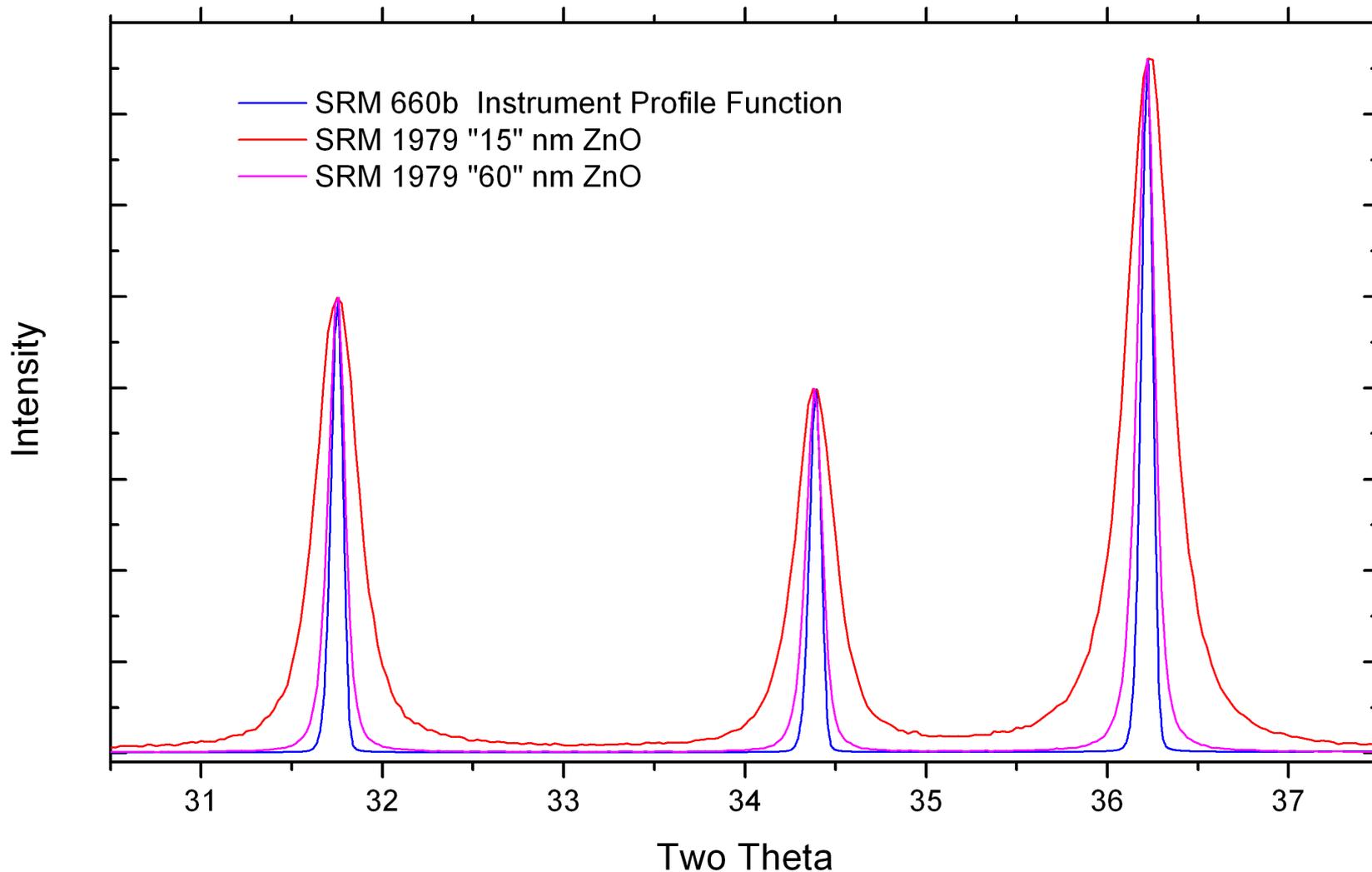
Refinement of SRM 660b LaB_6





Microstructure Analysis via Powder Diffraction

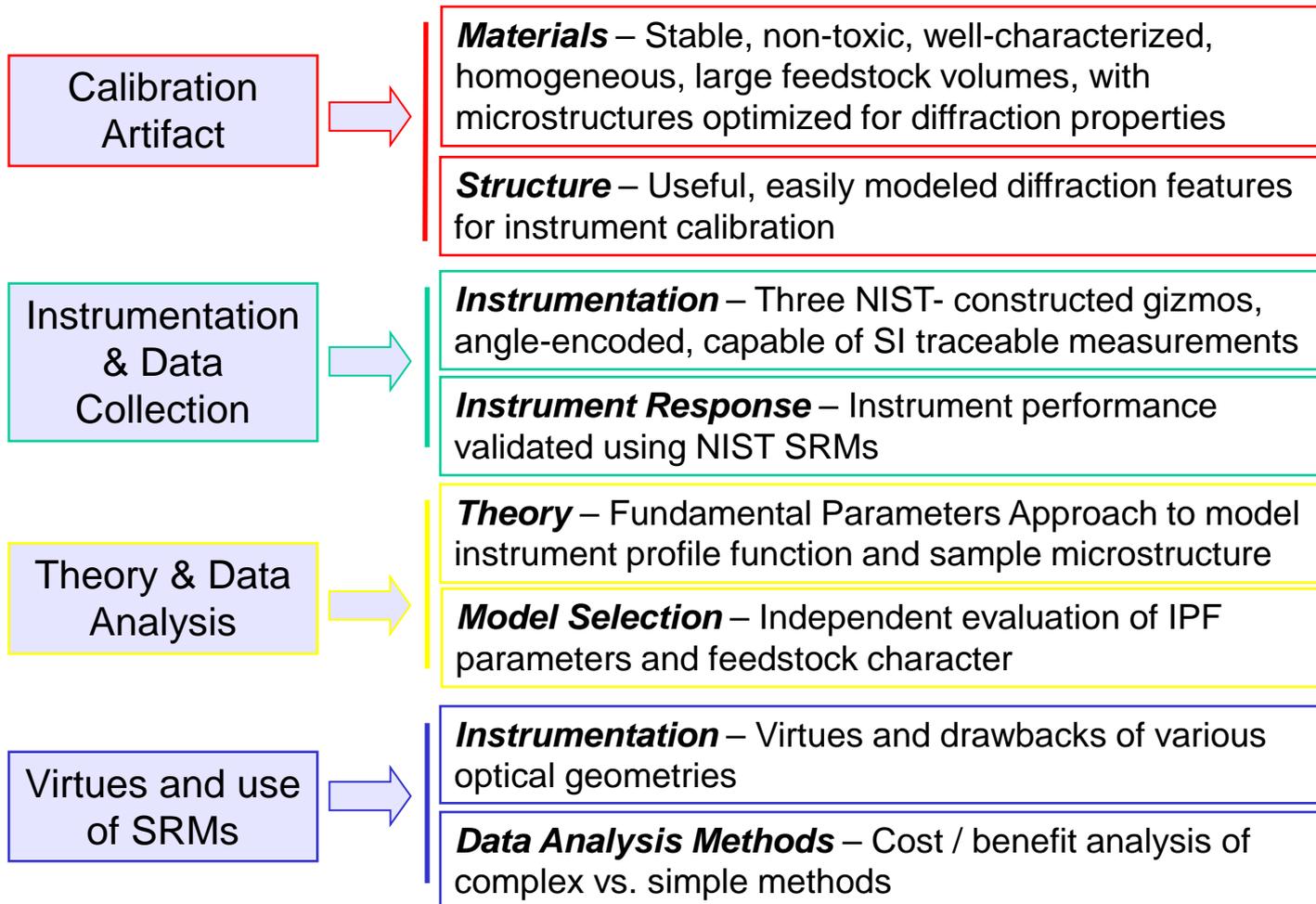
Crystallite size and lattice defect induced broadening of diffraction profiles





Certification of NIST Diffraction SRMs

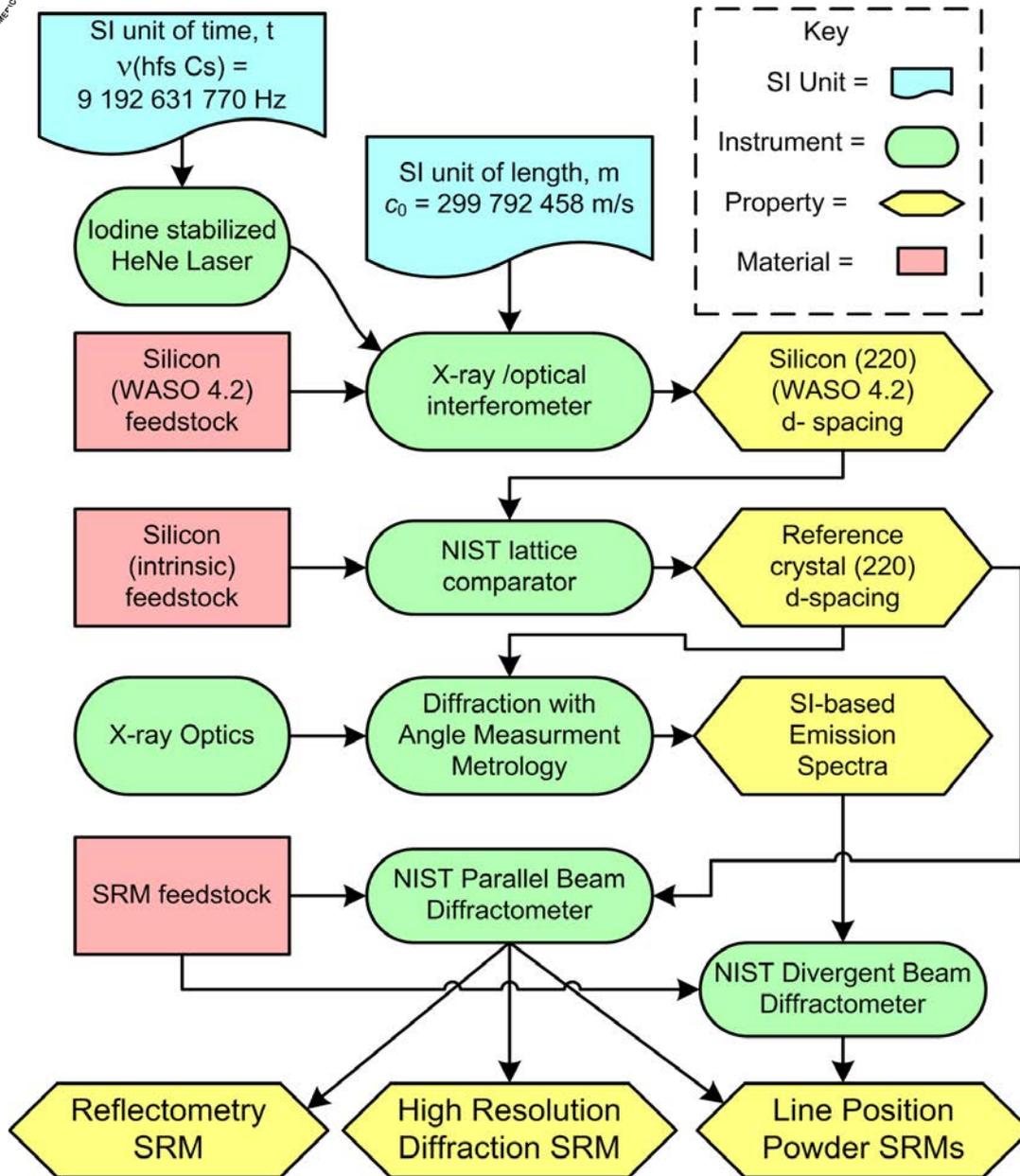
A technical approach with four primary facets





NIST SRMs for X-ray Wavelength Metrology

SRM	Material / Format	Diffraction Application	Unit Size (g)
640d	Silicon Powder	Line Position & Line Profile	7.5
675	Mica Powder	Line Position, Low 2θ	7.5
2000	Silicon (100) Wafer with SiGe Epilayer	High-Resolution Line Position & Reflectometry	25 mm square
660b	LaB ₆ Powder	Line Position & Line Profile	6
1979	ZnO Powders	Line Profile, 20 nm & 70 nm	3
1976b	Sintered Alumina Plate	Instrument Response	2.5 cm disc
676a	Alumina (corundum) Powder	Quantitative Analysis	20
674b	Powder Set: ZnO, TiO ₂ , CeO ₂ , & Cr ₂ O ₃	Quantitative Analysis	10 (each)
1878a	Respirable Quartz Powder	Quantitative Analysis	5
1879a	Respirable Cristobalite Powder	Quantitative Analysis	5
656	Silicon Nitride: α & β Powders	Quantitative Analysis	10 (each)



SI Traceability in Certification of Diffraction SRMs

$$\lambda = 2d \sin \theta$$

Angle metrology



Parallel Beam Diffractometer (PBD)

SI traceability / accuracy in wavelength and lattice parameter measurement

Measurement capability in HRXRD, XRR, and powder diffraction

Interchangeable optics and sample stages

Vertical axes, concentrically mounted
Huber 430 rotation stages

Heidenhain RON 905 optical encoders on
primary axes

Short and long range encoder calibration

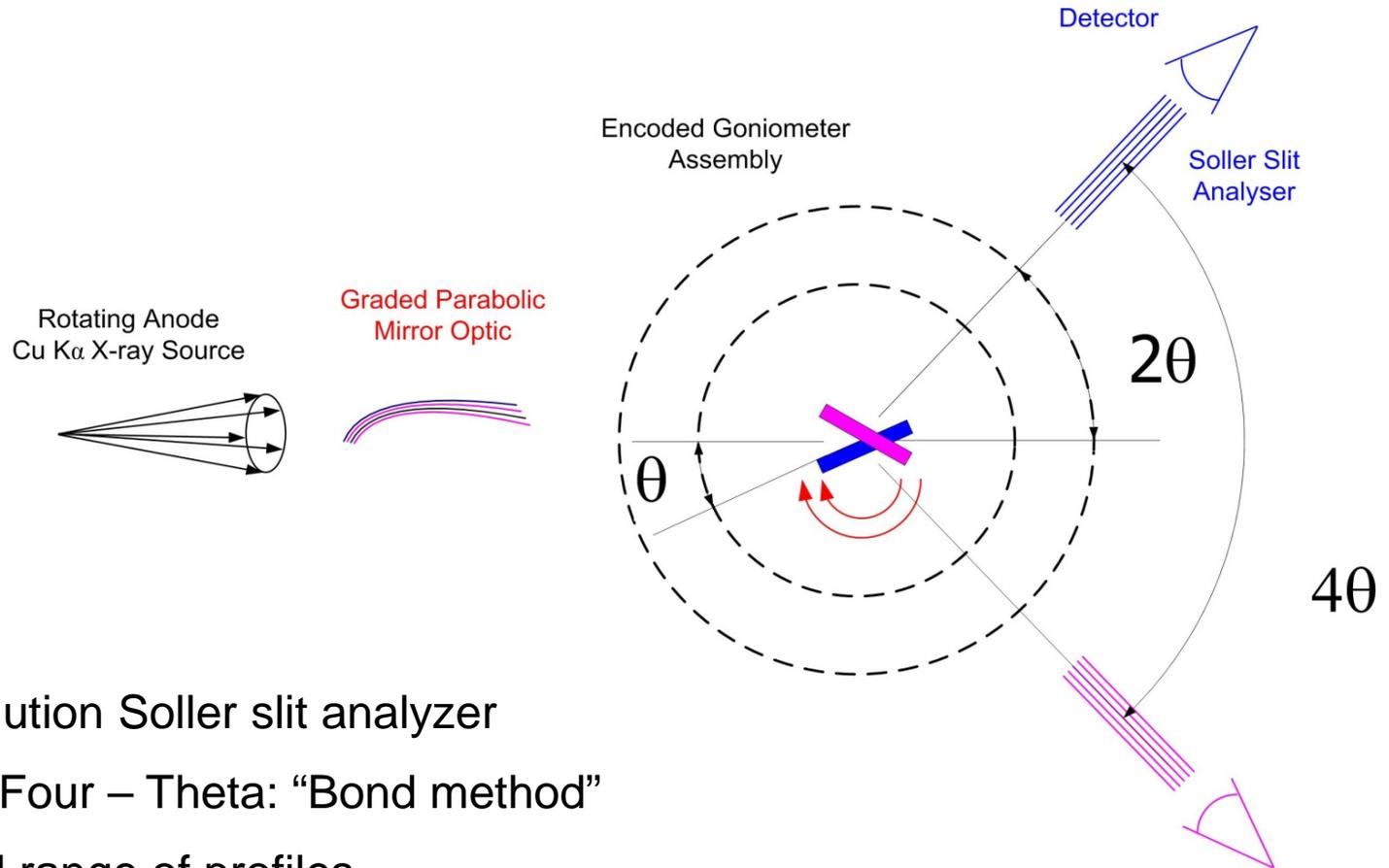
SI-traceable reference crystals

Located in temperature controlled
environment $\approx \pm 0.02^\circ \text{C}$





SI Traceable Measurement of Lattice Parameters on Powders with PBD



High-resolution Soller slit analyzer

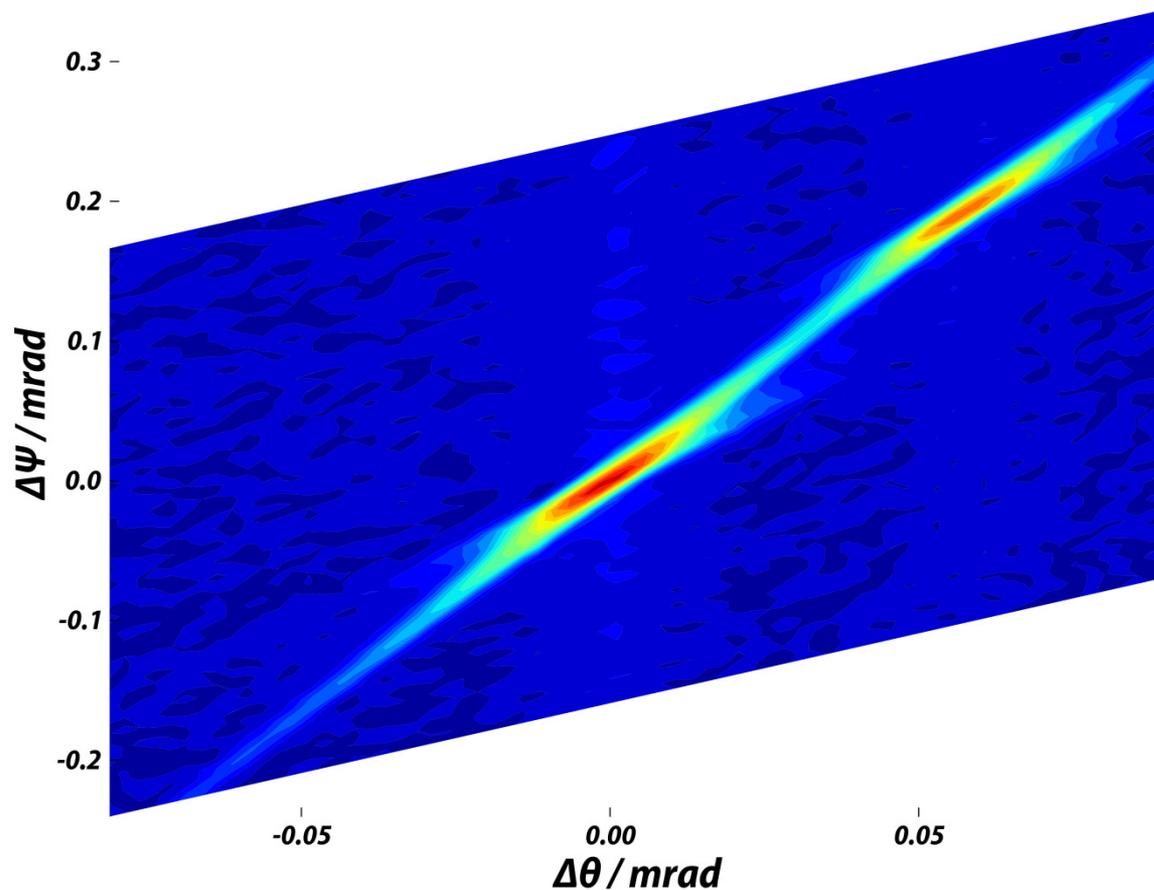
Measure Four – Theta: “Bond method”

Collect full range of profiles



Performance of Mirror Optic Determined via Double Crystal diffraction

Reciprocal space map illustrates divergence between $K\alpha_1$ and $K\alpha_2$ beam directions

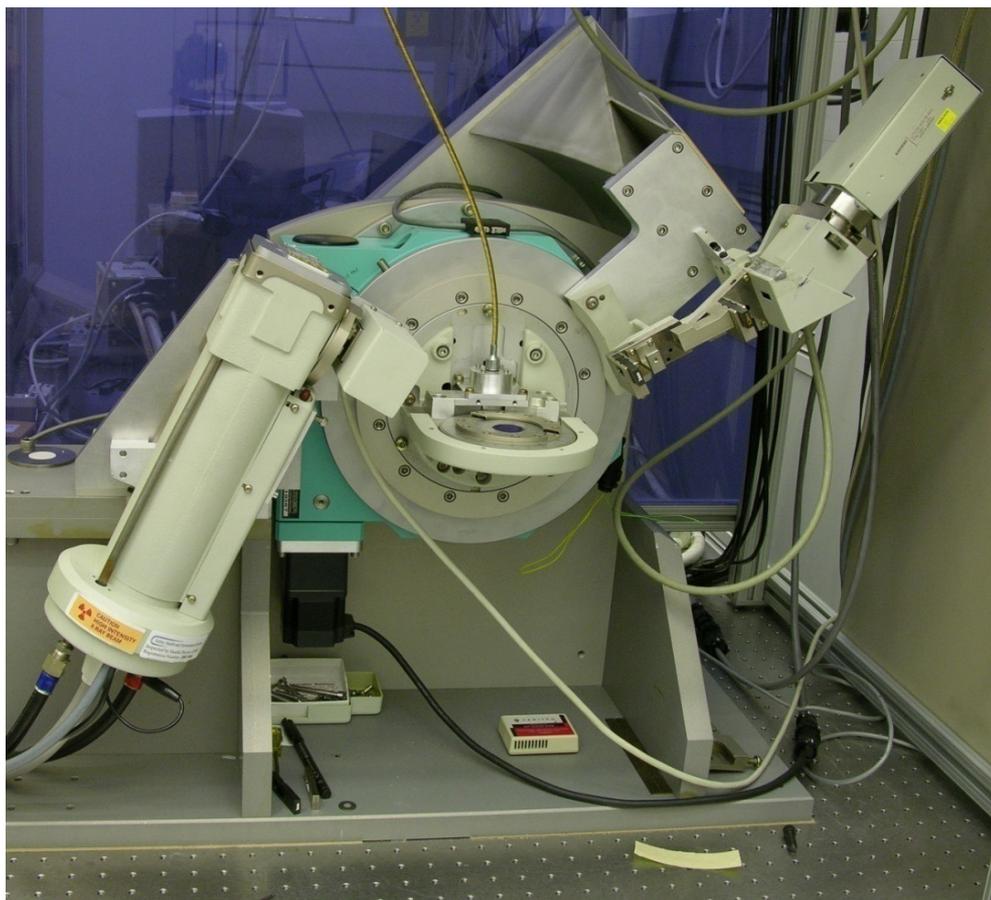




NIST – Built Divergent Beam Diffractometer (DBD)

Conventional divergent beam optics with high-performance goniometer

Second optical platform for corroboration of SI traceable measurements



Homogeneity verification
Studies of data analysis methods
Microstructure analysis

Optics from Siemens D5000 / D500

Huber 420 rotation stages

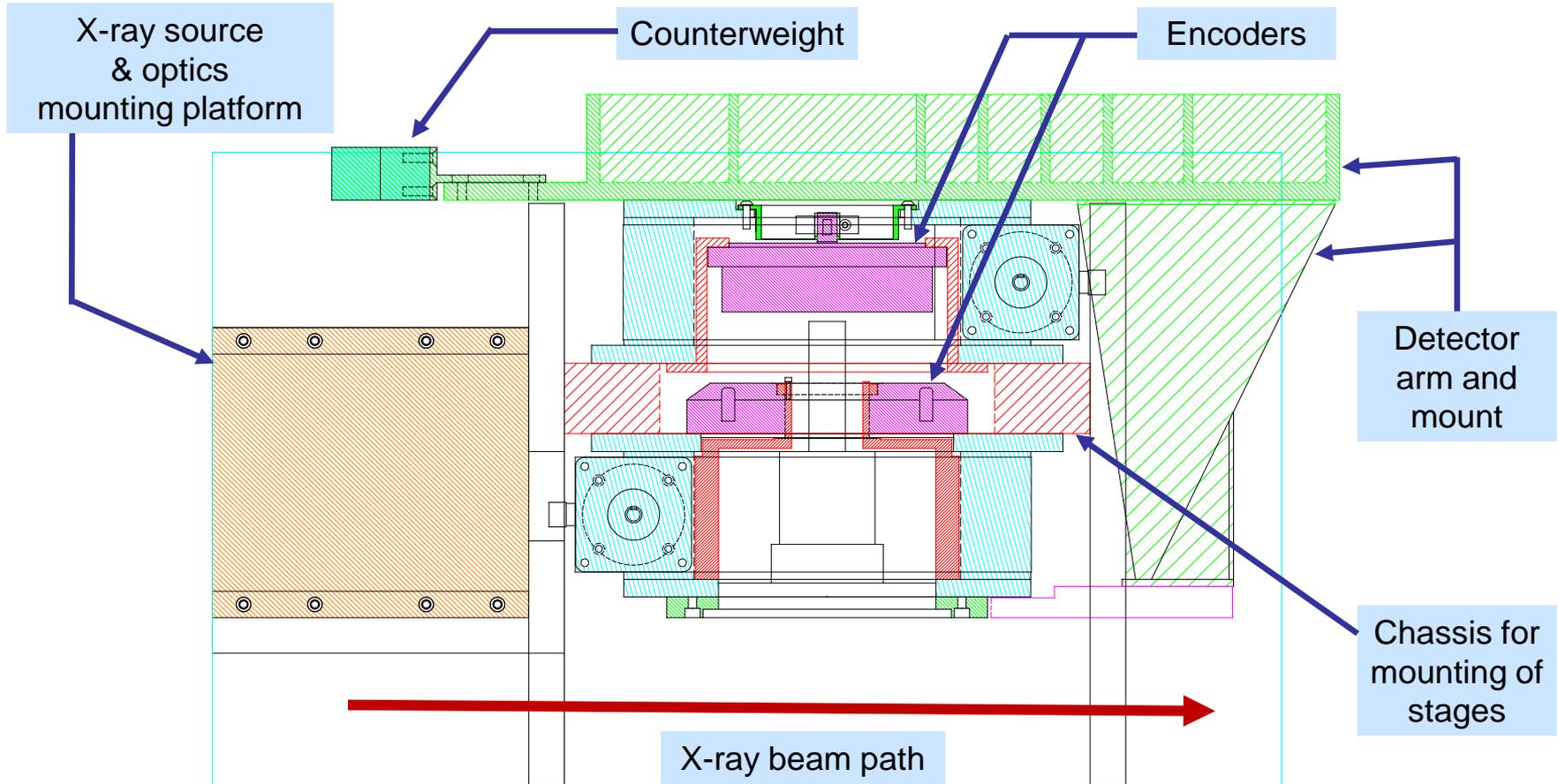
Heidenhain RON 800 series optical encoders on primary axes

Interchangeable optics,
Incident beam monochromator

Linear PSD

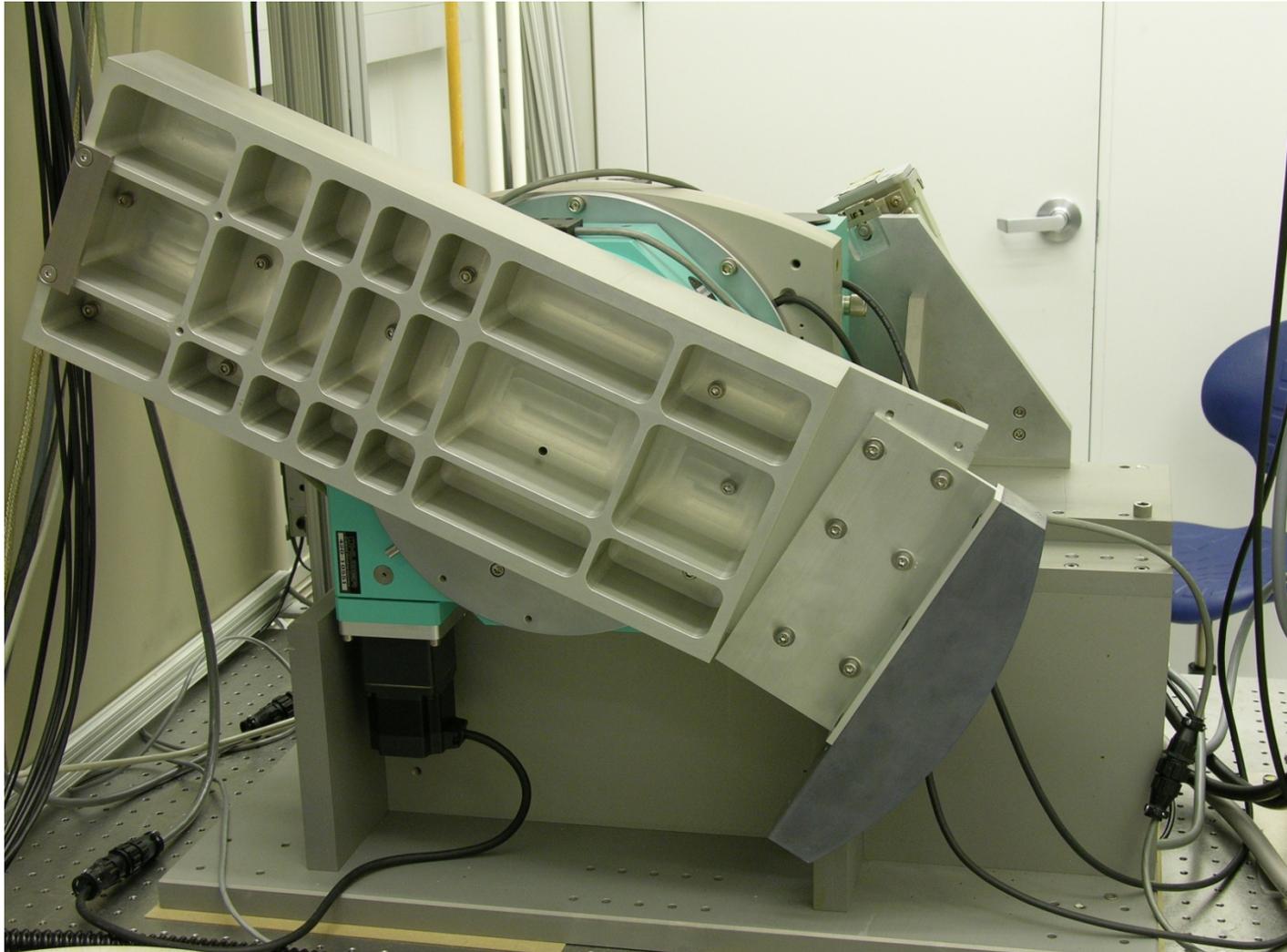
Located in a temperature controlled environment $\approx \pm 0.1^\circ \text{C}$

Overhead diagram of DBD





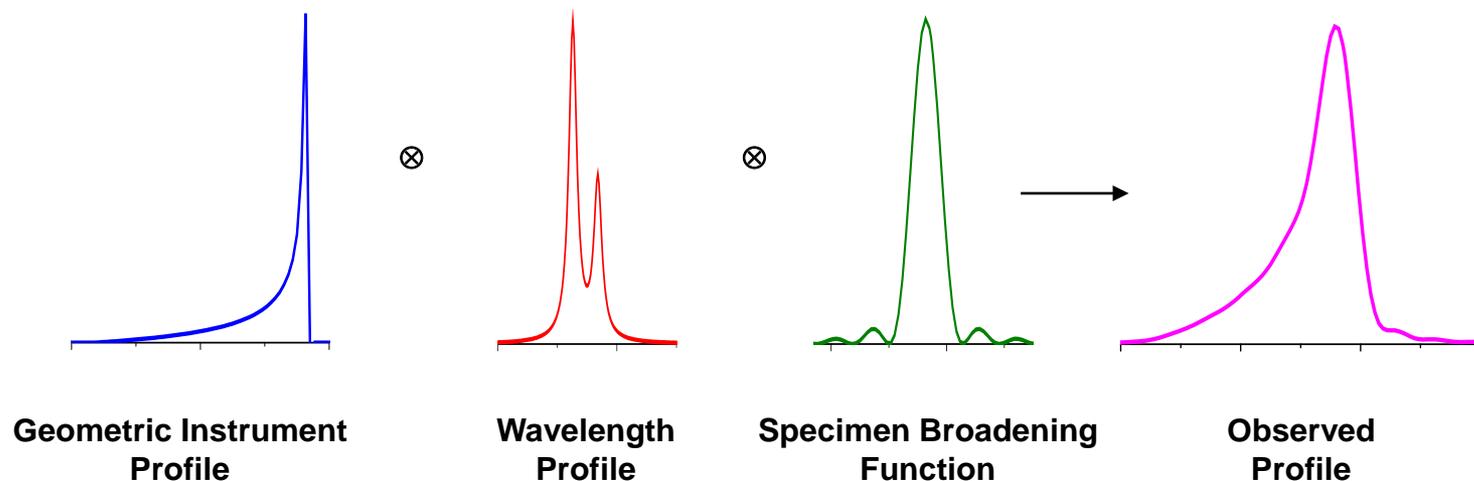
Stiff and Balanced Detector Arm





Fundamental Parameter Approach (FPA) to Analysis of Powder Diffraction Data

Cheary & Coelho (1992, 1998) as implemented in TOPAS

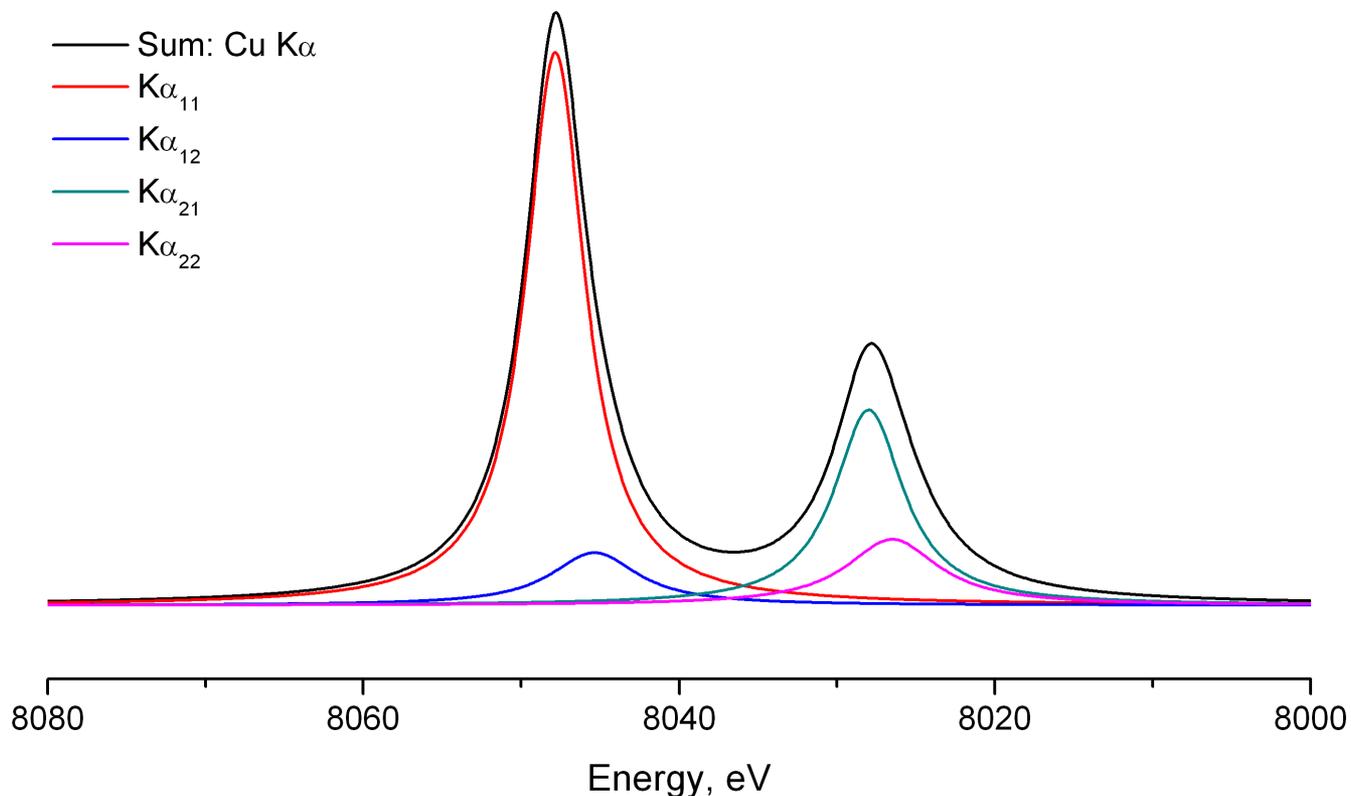


Geometric instrument contribution characterized with a series of explicit physical models linking instrument geometry to the observed profile



Current CuK α Emission Spectrum Characterization

Hölzer, *et al.*, Phys. Rev. A (1997)

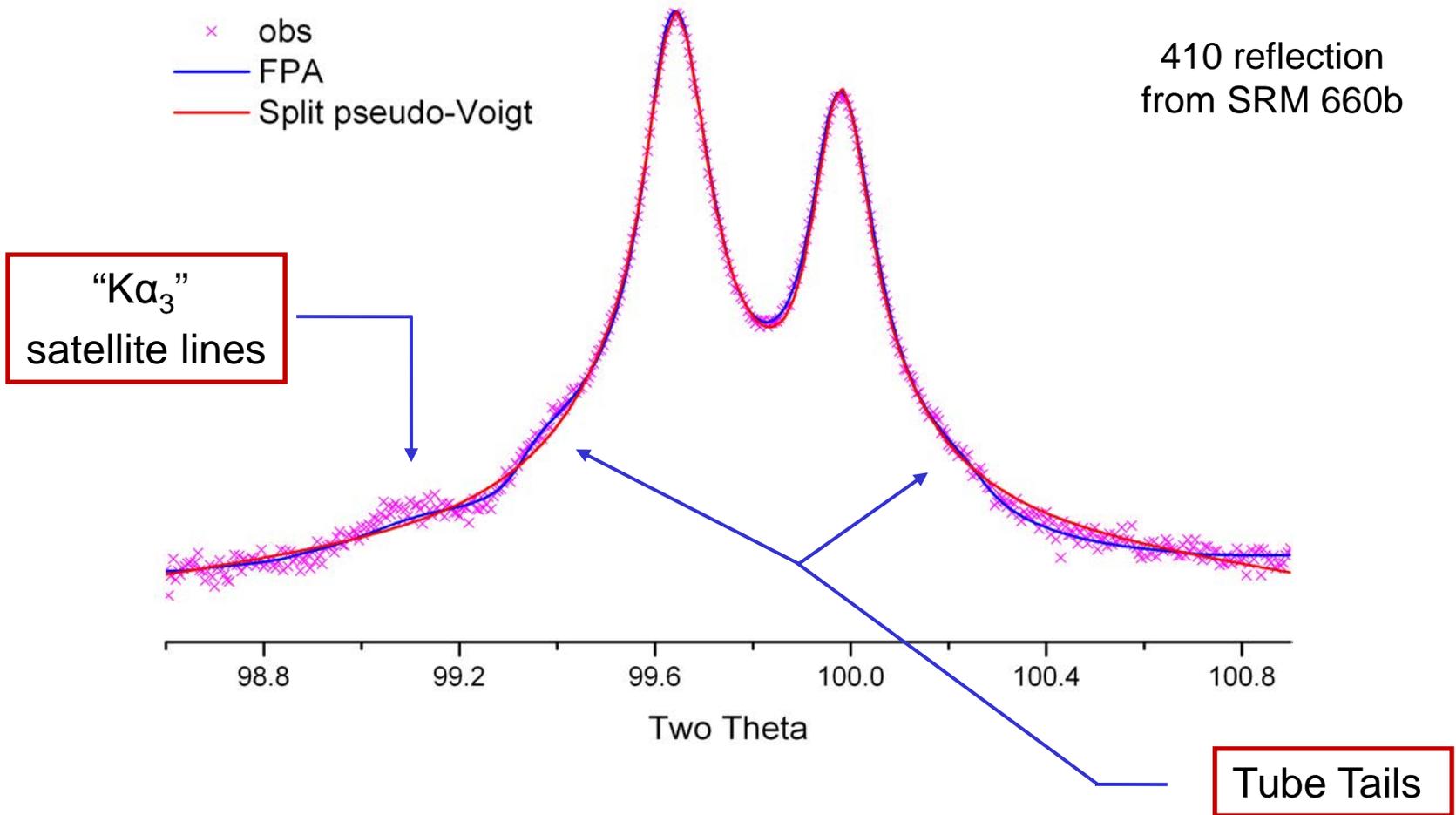


Four Lorentzian profiles used for analytical representation of the CuK α spectrum

Observation of Tube Tails & “K α_3 ” Satellite Lines

Proper modeling of tube tails critical for microstructure analysis

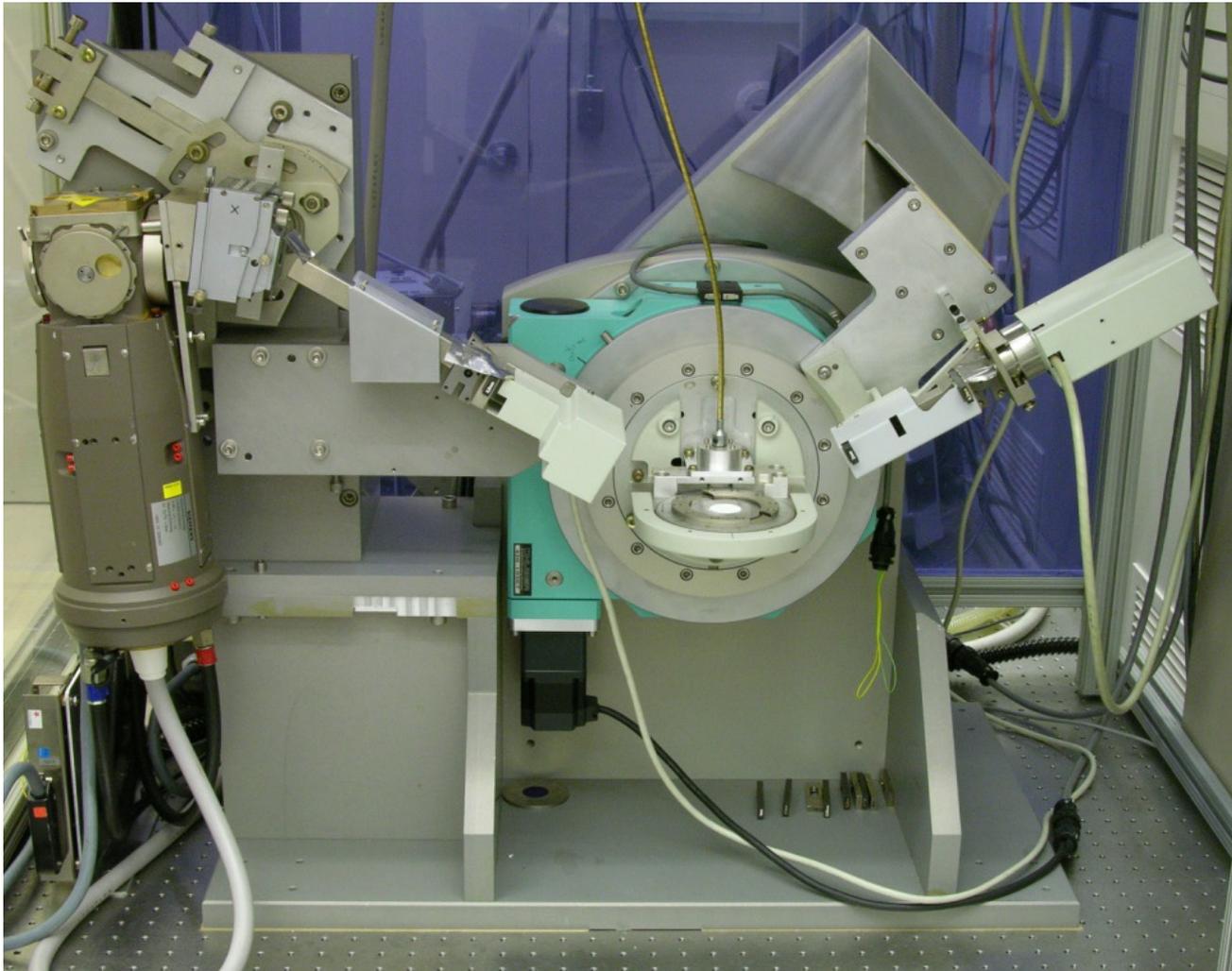
410 reflection
from SRM 660b





NIST – Built DBD Configured with Johansson IBM

Divergent beam optics with “monochromatic” source



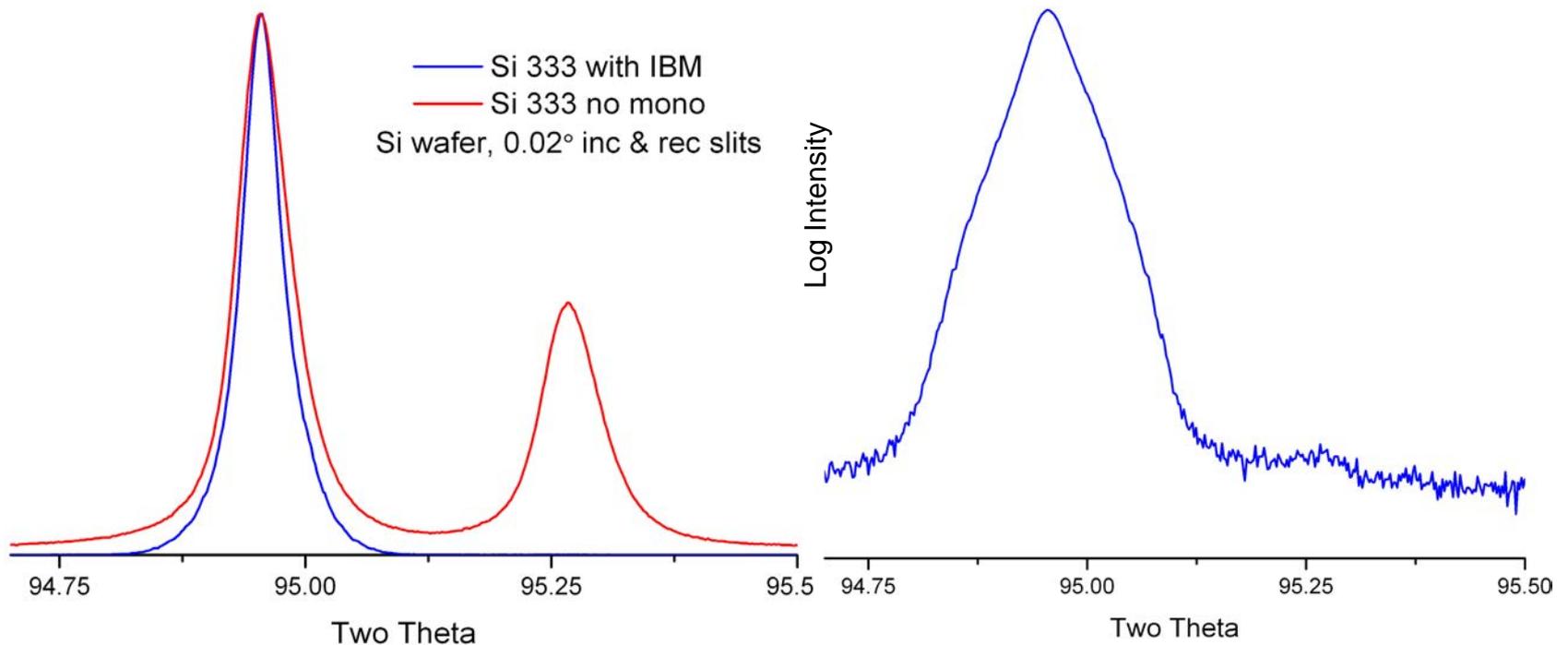
Siemens D500 tube shield with Huber 502 optic alignment:
Features fully orthogonal adjustment capability

Modern Crismatec Johansson optic



Performance of Johansson IBM

Crismatec (Saint Gobain) Johansson optic
Ge 111 crystal bent via cementing in pre-form

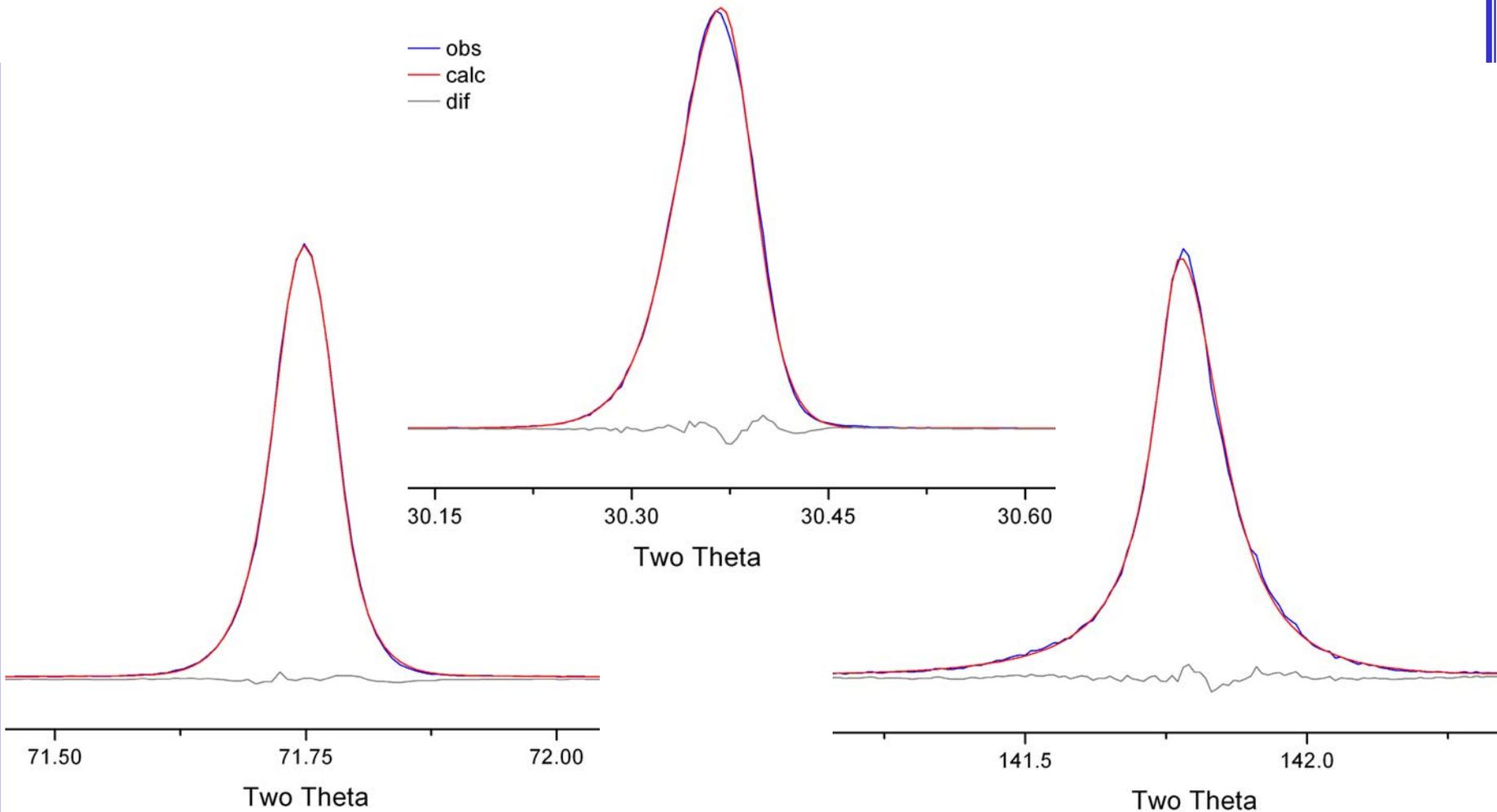


Characterization of emission spectrum for *FPA* via convolution of Gaussian profile shape functions



Fits of Split Pearson 7 PSF to IBM data

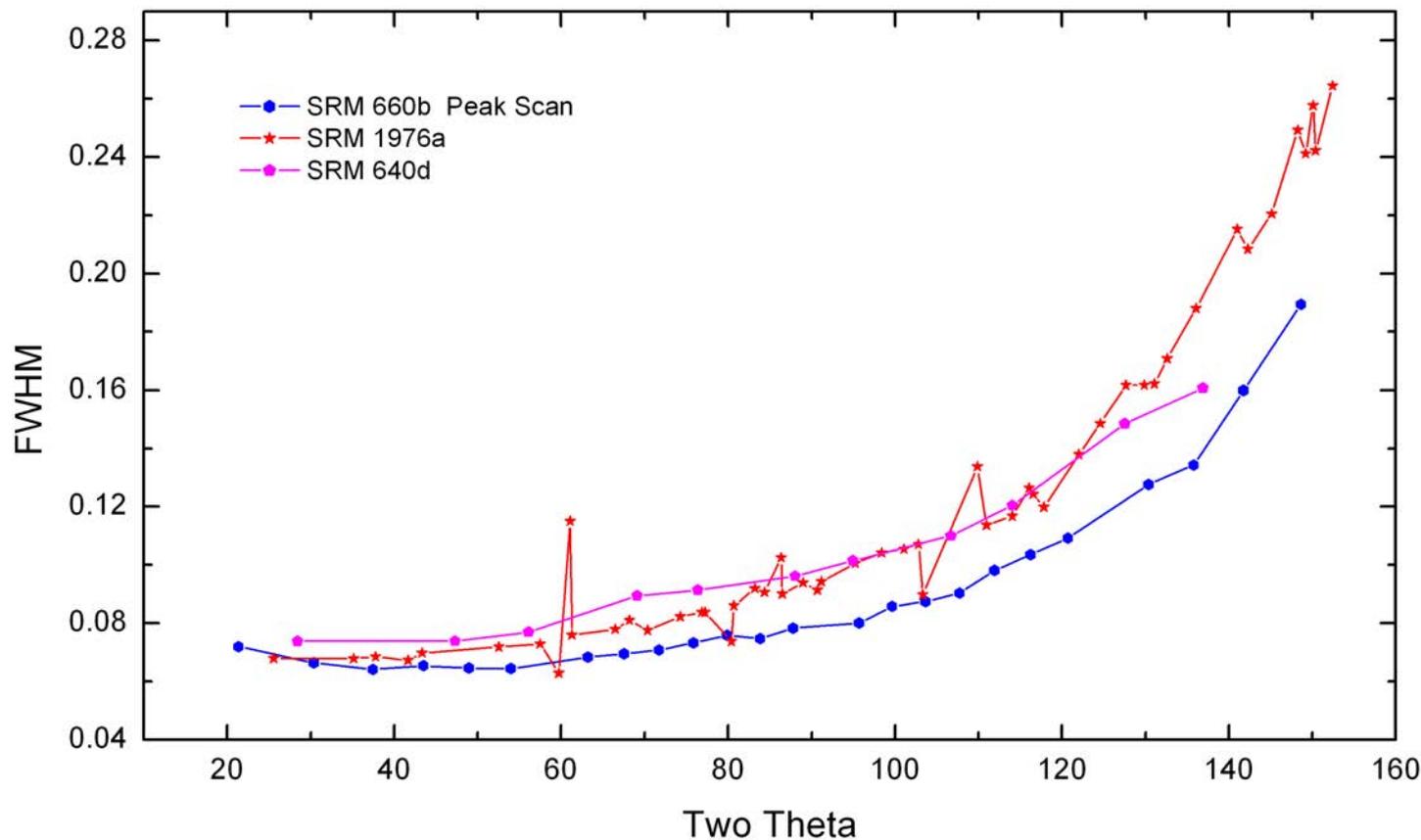
Excellent fit quality to IBM data using analytical PSF





FWHM data from SRMs 640d, 660b and 1976b

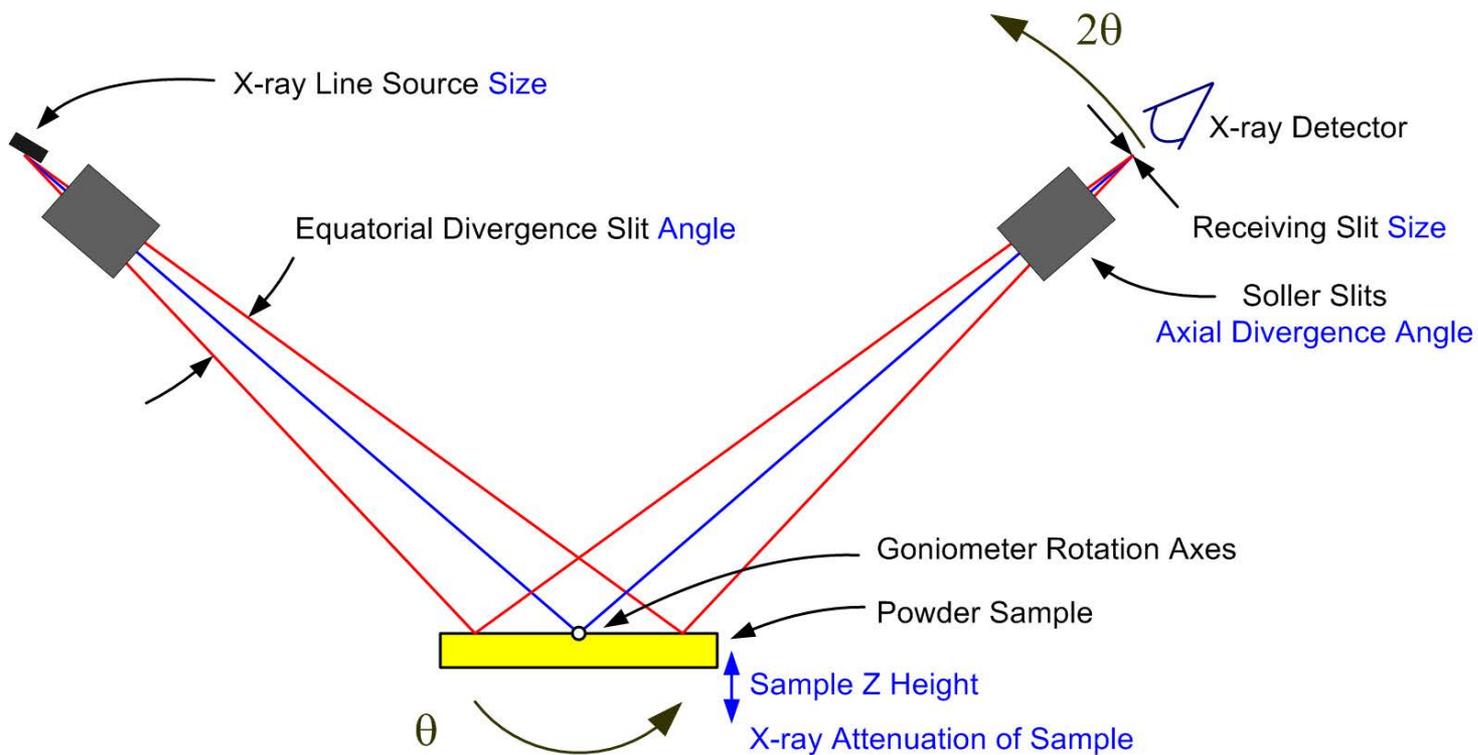
FWHM values follow trends consistent with expectations as per contributions from Geometric and Wavelength Profiles





Parameters Affecting Geometric Profile

Divergent beam laboratory X-ray powder diffractometer





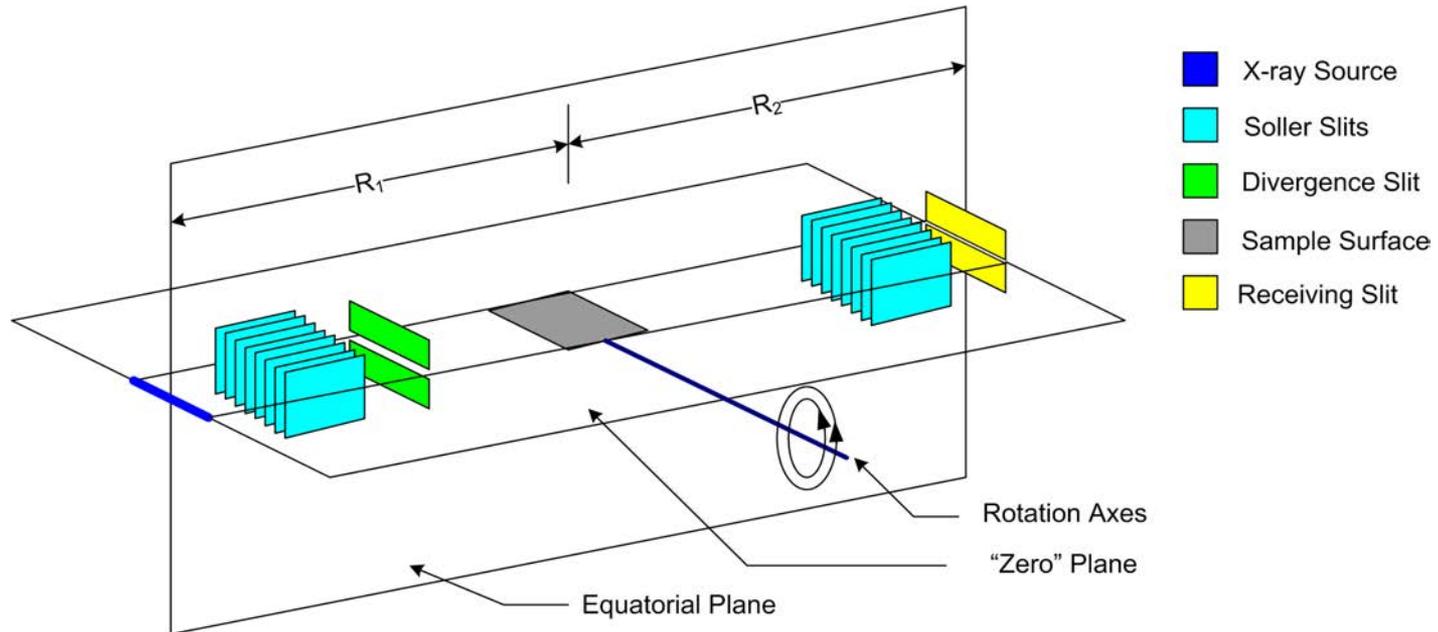
Aberrations Contributing to Geometric Component

May affect both profile shape and position

Aberration	Controlling parameters	Impact
X-ray Source Width (w_x)	Angle subtended by source: $\frac{w_x}{R}$	Symmetric broadening
Receiving Slit Width (w_r)	Angle subtended by slit: $\frac{w_r}{R}$	Symmetric broadening
Flat Specimen Error / Equatorial Divergence	Angle of divergence slit: α	Asymmetric broadening to low 2θ , with decreasing 2θ
Axial Divergence Case 1: No Soller slits Case 2: Soller slits define divergence angle	Axial lengths of the x-ray source (L_x) sample (L_s) & receiving slit (L_r) relative to goniometer radius (R) Acceptance angles Δ_I and Δ_D of the incident and diffracted beam Soller slits	Below $\approx 110^\circ$: Asymmetric broadening to low 2θ , with decreasing 2θ Else to high 2θ , with increasing 2θ
Specimen transparency	Penetration factor relative to diffractometer radius $\frac{1}{\mu R}$	Asymmetric broadening to low 2θ , with $\text{Sin}(\theta)$
Specimen Displacement Z height	Displacement of specimen surface from goniometer rotation axes	Displacement of profiles with $1/\text{Cos}(\theta)$

Diagram of an Aligned X-ray Diffractometer

Functionality of FPA dependent on proper alignment



Requisite on:

- 1) Source-to-sample distance equals sample-to-receiving slit distance ($R_1 = R_2$)
- 2) X-ray line source, sample, and receiving slit centered in plane of diffraction
- 3) Goniometer rotation axes are co-axial
- 4) X-ray line source, sample surface, receiving slit, and goniometer rotation axes are co-planar, in the "zero" plane, at zero angle of theta and two-theta
- 5) Incident beam is centered on both equatorial and "zero" planes

X-rays off

X-rays on



Data Analysis Strategy

Determine extent and nature of flaws in FPA model

Compare refined lattice parameters from FPA Rietveld analysis with those from FPA “Profile” analysis

Always refine parameters that are indeterminate
Sometimes refine parameters that are known or essentially invariant between standards and unknowns
Never refine parameters that well known and correlate with unknowns

Always Refine:
Axial divergence value
[inc and rec values constrained to identity]
Z height
Specimen transparency
Position & intensity of $K\alpha_2$ lines
Structural model(s)
Microstructure model(s)

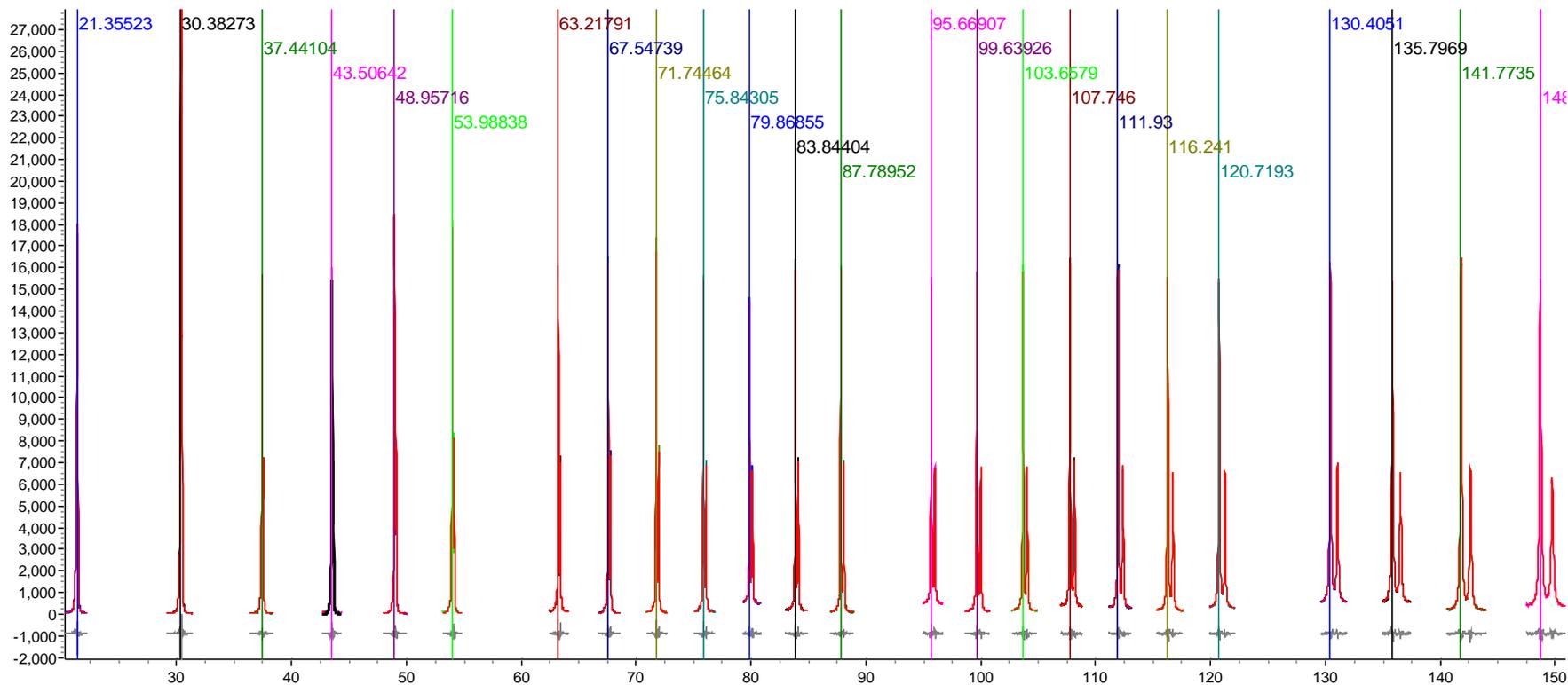
Sometimes Refine:
Breadth of $K\alpha_1$ and $K\alpha_2$ lines
Inc and rec slit values
“Tube Tail” parameters
“ $K\alpha_3$ ” line intensity

Never Refine:
Zero angles



Fundamental Parameters Analysis of SRM 660b

FPA “profile” analyses: Profile positions (lattice parameters) free to refine, FPA shape parameters constrained

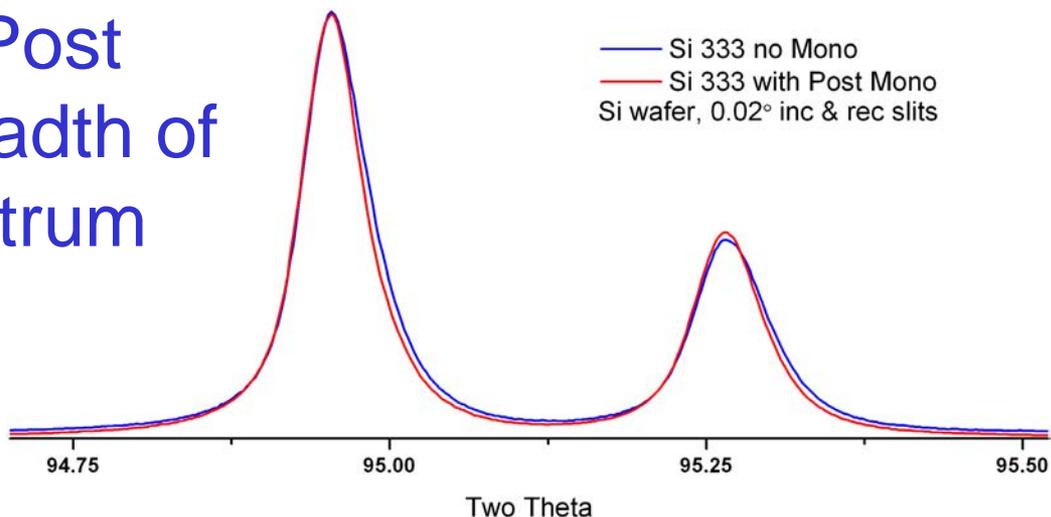


Plausible parameters realized throughout *



Impact of Graphite Post Monochromator on Breadth of CuK α Emission Spectrum

20% Reduction in breadth
Shift of 0.01°



```

for xdds {
  LP_Factor( 26.6).
  lam.
  ymin_on_ymax 0.0001.
  la sat 0.0080`_0.000213173601 lo 1.534753 lh 3.6854.
  la 0.5711 lo 1.540591 lh lh11 0.3314`_0.00240437679.
  la 0.0781 lo 1.541064 lh =lh11 1.47; : 0.4871`_0.00353443388.
  la la21 0.2565`_0.000255806605 lo l21 1.544386`_4.98191335e-007 lh lh21 0.4022`_0.00261264019.
  la =la21 .36; : 0.0923`_9.20903777e-005 lo =l21+.0003; : 1.544686`_4.98191335e-007 lh =lh21 1.4; : 0.5631`_0.00365769627.
  Specimen_Displacement(-0.00192).
  x_calculation_step = Yobs_dx_at(Xo); convolution_step 4.
  Rp 217.5.
  Rs 217.5.
  Slit_Width( 0.2).
  Divergence( 0.8).
  axial_conv .
  filament_length 12.
  sample_length 15.
  receiving_slit_length 15.
  primary_soller_angle ssl 5.3752411`_0.00751067001.
  secondary_soller_angle ssl 5.3752411`_0.00751067001.
  axial_n_beta 30.
  Tube_Tails(, 0.04,ttl, -1.06559`_0.00431,tt2, 1.18058`_0.00390,ttf, 0.00102`_0.00025).
  Absorption(672.35363).
  
```

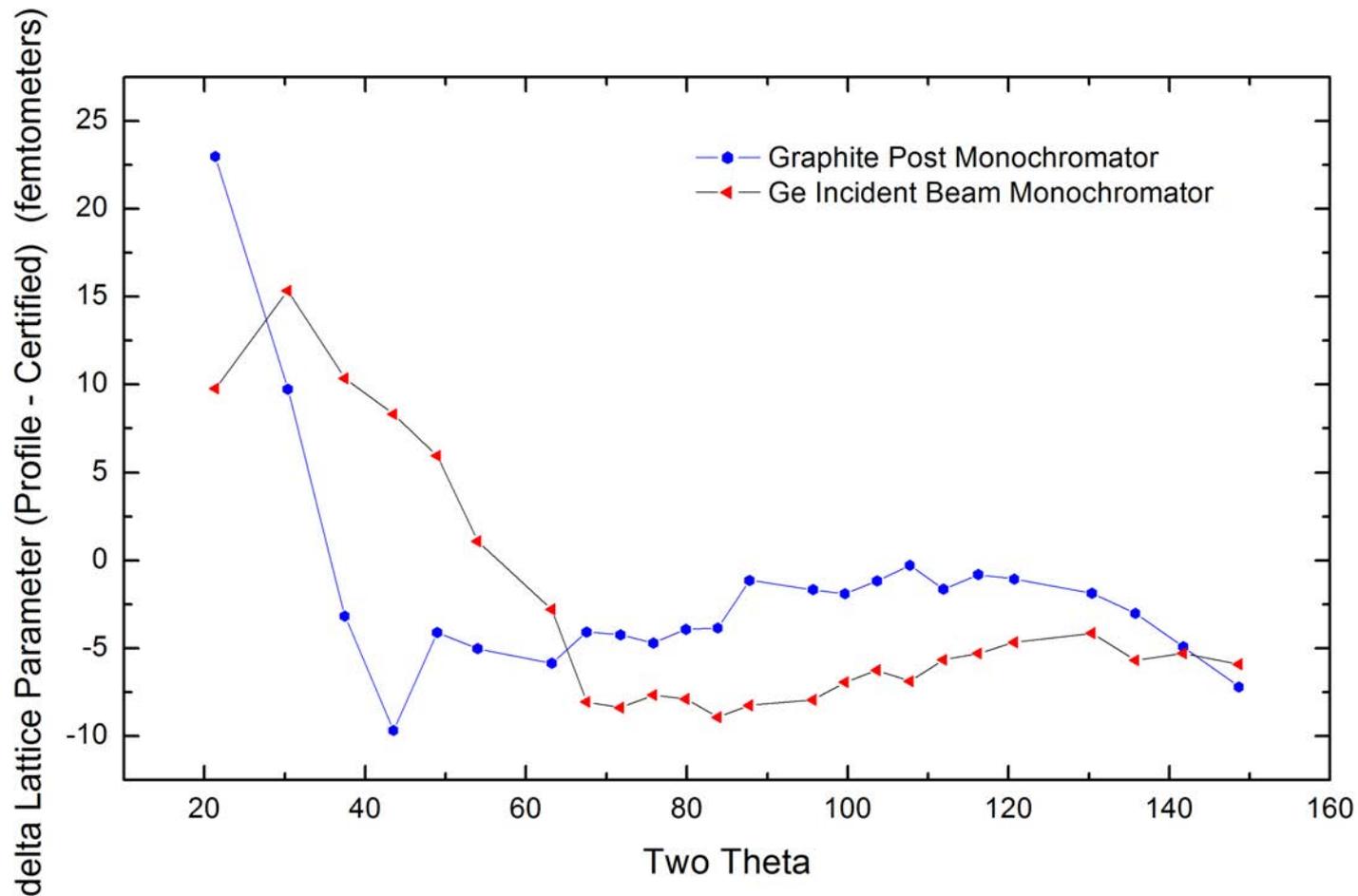
Portion of Topas .inp file illustrating refinement of profile breadths
Shape of $K\alpha_1$ and $K\alpha_2$ lines constrained to that defined by Hölzer





Comparison of Lattice Parameter Data from FPA Rietveld vs. Profile

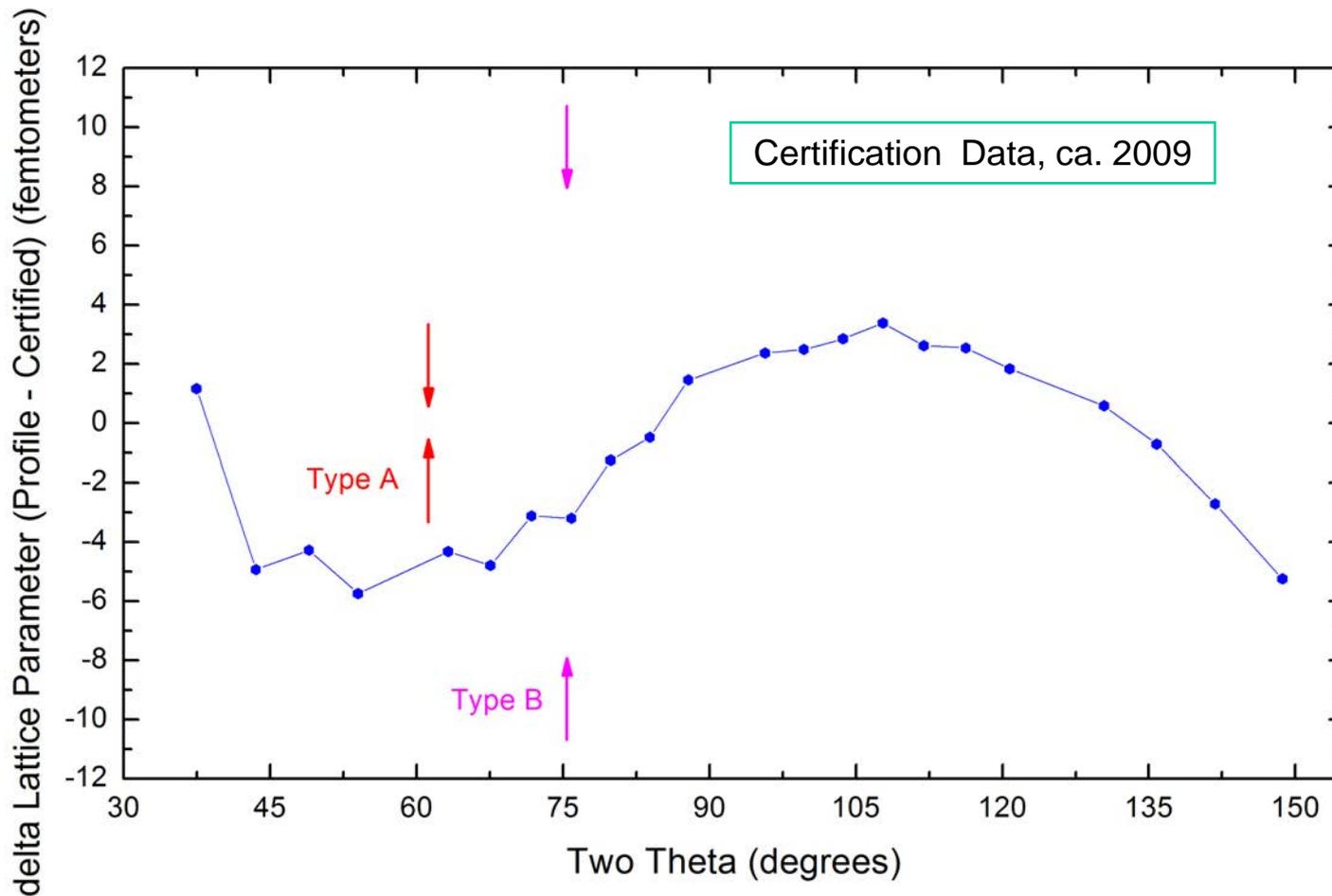
No Complaints; However, trends are indicated





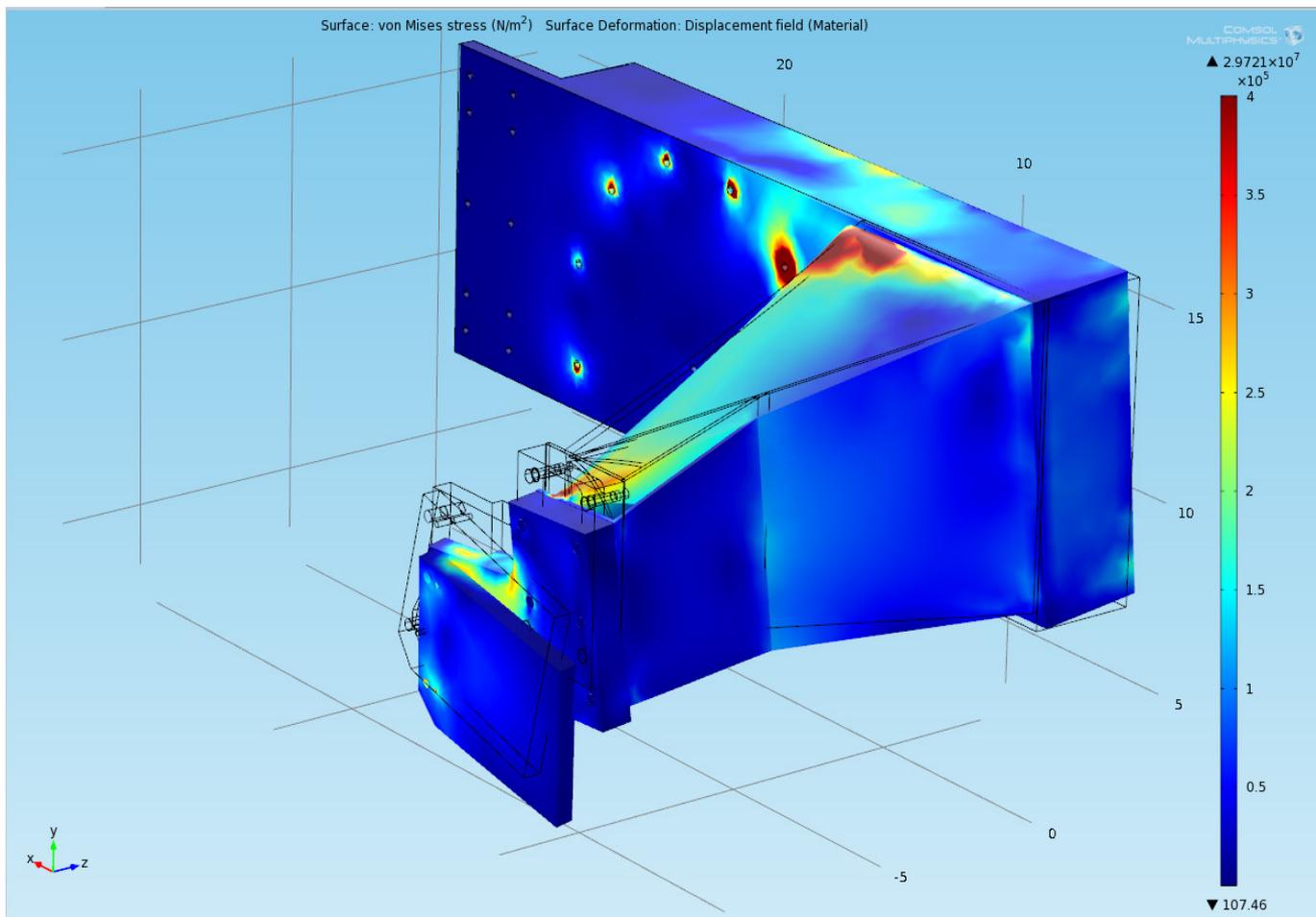
Comparison of Lattice Parameter Data from FPA Rietveld vs. Profile: Certification of SRM 660b

Type A (statistical) vs. Type B (systematic) error bounds





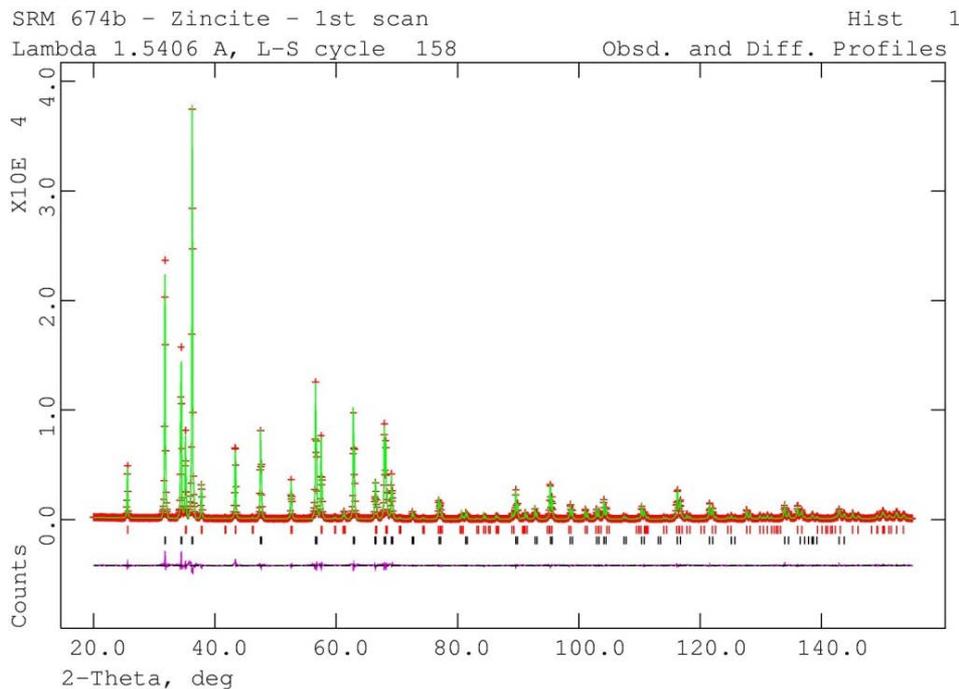
Finite Element Analysis of Change in Torque Moment with Rotation of Two-Theta Arm





Quantitative Rietveld Analysis, QRA

Diffraction experiment assesses crystalline component only



Quantification via GSAS:

$$\frac{X_{\alpha}}{\sum_{k=1}^n X_k} = \frac{S_{\alpha} Z_{\alpha} w_{\alpha}}{\sum_{k=1}^n S_k Z_k w_k}$$

X_{α} is the mass fraction of phase α
 S_k are the scale factors
 w_k are the molecular weights
 Z_k are the number of formula weights per unit cell

$$\sum_{k=1}^n X_k = 1$$

Suitable Standard: $X_s = X_{s(xtal)} + X_{s(amor)}$ Yields:

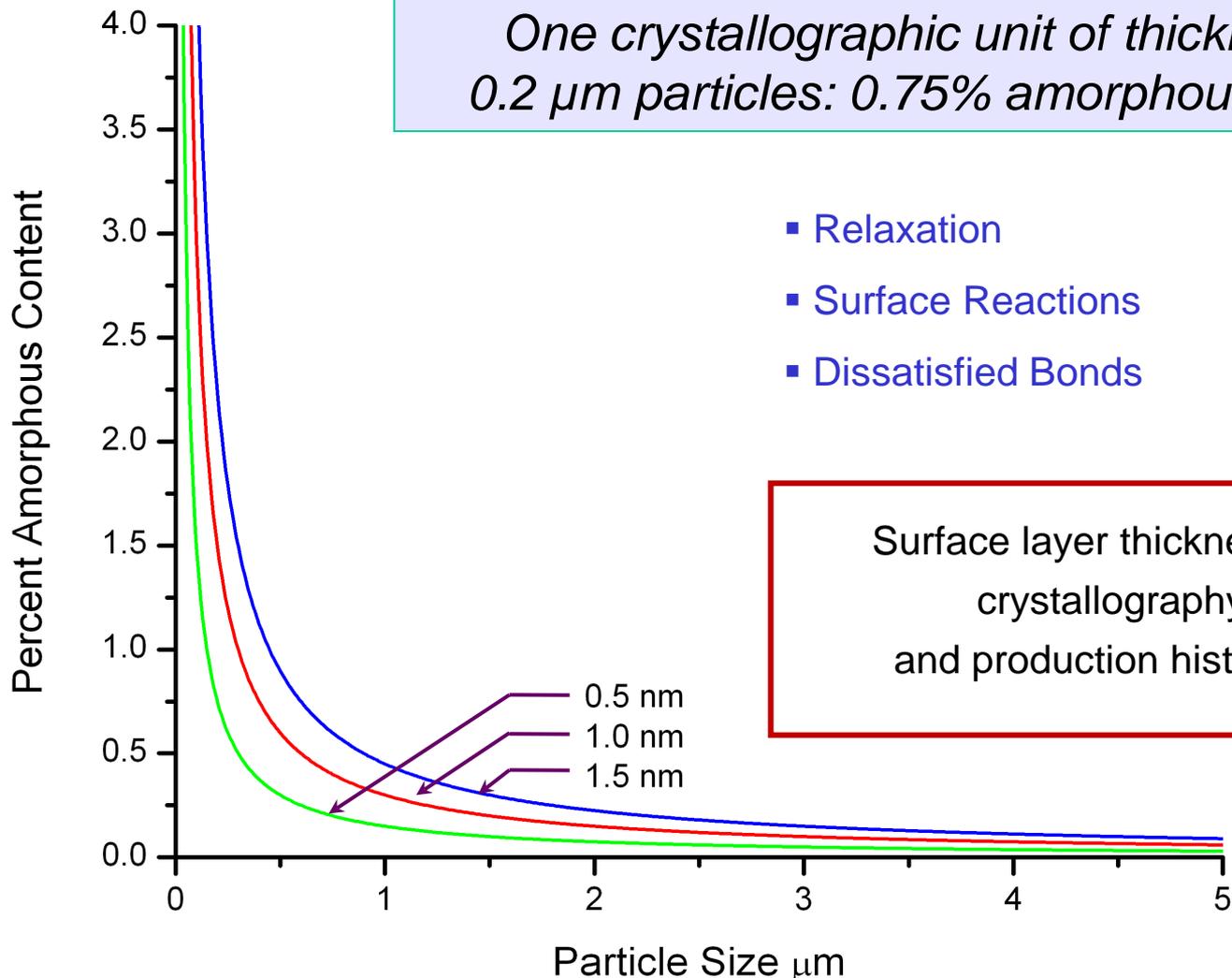
$$\frac{X_{s(xtal)}}{\sum X_{u(xtal)} + X_{s(xtal)}} = \frac{S_s Z_s w_s}{\sum S_k Z_k w_k}$$

$$\sum X_{u(xtal)} + X_{u(amor)} = 1 - X_s$$



Amorphous Component of Finely Divided Crystalline Solids

One crystallographic unit of thickness on 0.2 μm particles: 0.75% amorphous content



- Relaxation
- Surface Reactions
- Dissatisfied Bonds

Surface layer thickness determined by crystallography, chemistry and production history of the powder



Selection of an Alumina Powder for use as an Internal Intensity (Quantitative Analysis) Standard

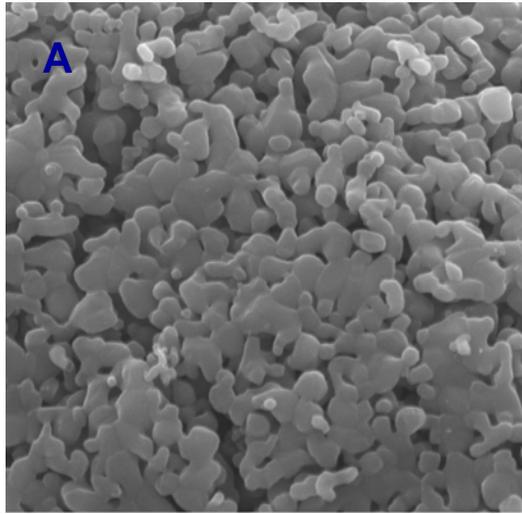
I/I_c Proposed by Visser and deWolff (1964)

Property included in ICDD database; hence SRM 676(x)

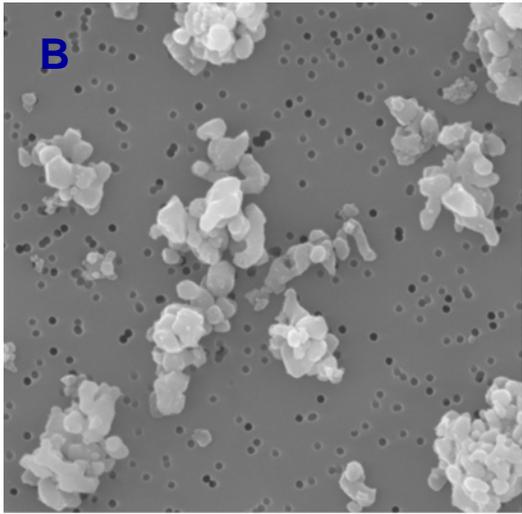
Desired characteristics of SRM feedstock

- strong lines over a wide d-space range
- stability
- inertness
- equi-axial (non-orienting) particles
- particle size in the one micrometer range: microabsorption (Brindley, 1945)
- small diffracting domains: primary extinction (Zachariasen, 1945)

Selection of an Alumina Powder for use as an Internal Intensity Standard



2µm 10000X



2µm 10000X

Commercial Alumina Production
95% via Bayer process:



Low T: Transition alumina impurities “Active Alumina”
High T: Platelike coarse grains “Tabula Alumina”

Material not well suited for use as a standard

Dynys and Halloran (1982) :



Low T: Phase pure alumina w/ “sponge” microstructure **A**
With comminution: Equiaxial fine grains **B**

Material quite well suited for use as a standard



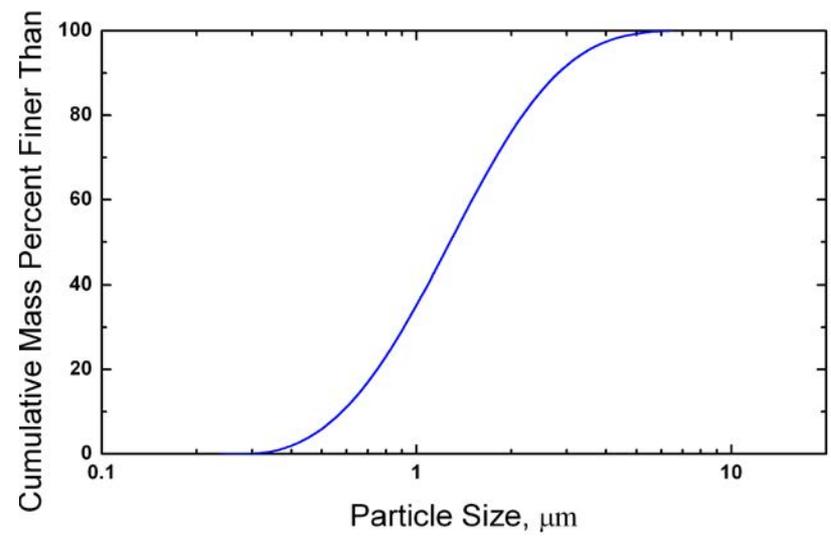
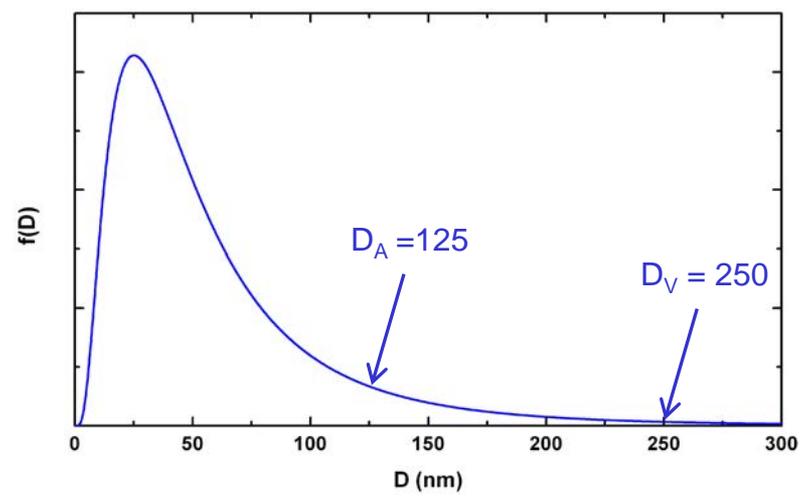
SRM 676a Feedstock Consists of Baikalox* CR1

Alum process Calcined to 1400°C Jet milled

Particle size via laser scattering

%<	μm
10	0.58
50	1.28
90	2.82

*Baikowski Chimie, France



Crystallite size via profile broadening
Data from 11 BM, APS, SRMs 660a & 676a
Analysis via TOPAS
Distribution via Krill & Birringer (1998)
Popa & Balzar (2002)
Implementation via P. Whitfield



Determination of Amorphous Fraction I

Diffraction experiment: crystalline fraction only
Weighing operation: all constituents

Experimental Design

No possibility for phase pure reference material

Vary impurity level in systematic manner

Engineer microstructure so as to ensure said variation

Single crystal reference material; as per silicon of SRM 640c

Amorphous material restricted to surface (oxide) layer

Surface layer of uniform thickness, invariant with respect to particle size

Variation of particle size / surface area in series of single crystal powders

Diffraction experiments on series of two phase mixtures, reference vs. test

Extrapolate diffraction results to reference phase of “zero” amorphous content

Compare diffraction result from test phase to mass fraction of weighing operation



Determination of Amorphous Fraction II

Execution

- Comminute silicon to broad size distribution & anneal
 - Fractionate into five lots from 5 - 25 micrometers
 - Measure surface area & particle size
 - Prepare 4 X 50-50 mixtures, plus SRM 640c

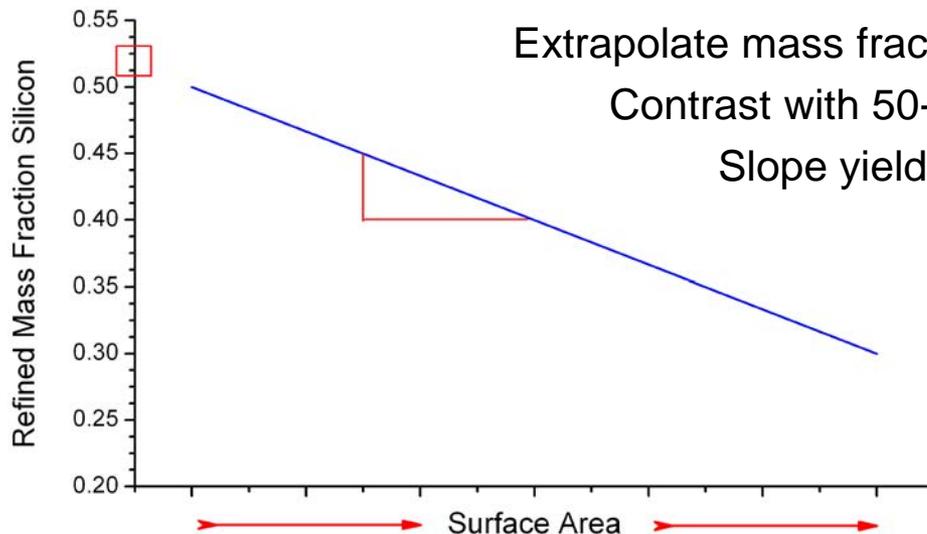
- Accurate diffraction experiments
 - Multiple diffraction methods/facilities
 - Address extinction effects within QRA

Plot refined mass fraction silicon vs. surface area

Extrapolate mass fraction trend to a silicon with “zero” surface area

Contrast with 50-50 mass fraction: phase purity of SRM 676a

Slope yields oxide layer thickness on silicon





Microstructure Data on the Five/Six Lots of Silicon

Sieve Fraction	SRM 640c	< 5 μm	5 < 10 μm	10 < 15 μm	15 < 20 μm	20 < 25 μm
Particle Size, μm	4.44	5.28	9.81	14.47	19.24	23.98
Surface Area, m^2/g	1.40	1.50	0.70	0.41	0.31	0.27

Annealed in gettered argon at 1000°C for 2 h, van Berkum, et al. (1995)

Electro-deposited sieves, 5,10,15,20 & 25 μm

Sieved in anhydrous isopropyl alcohol, wash w/ dilute nitric acid

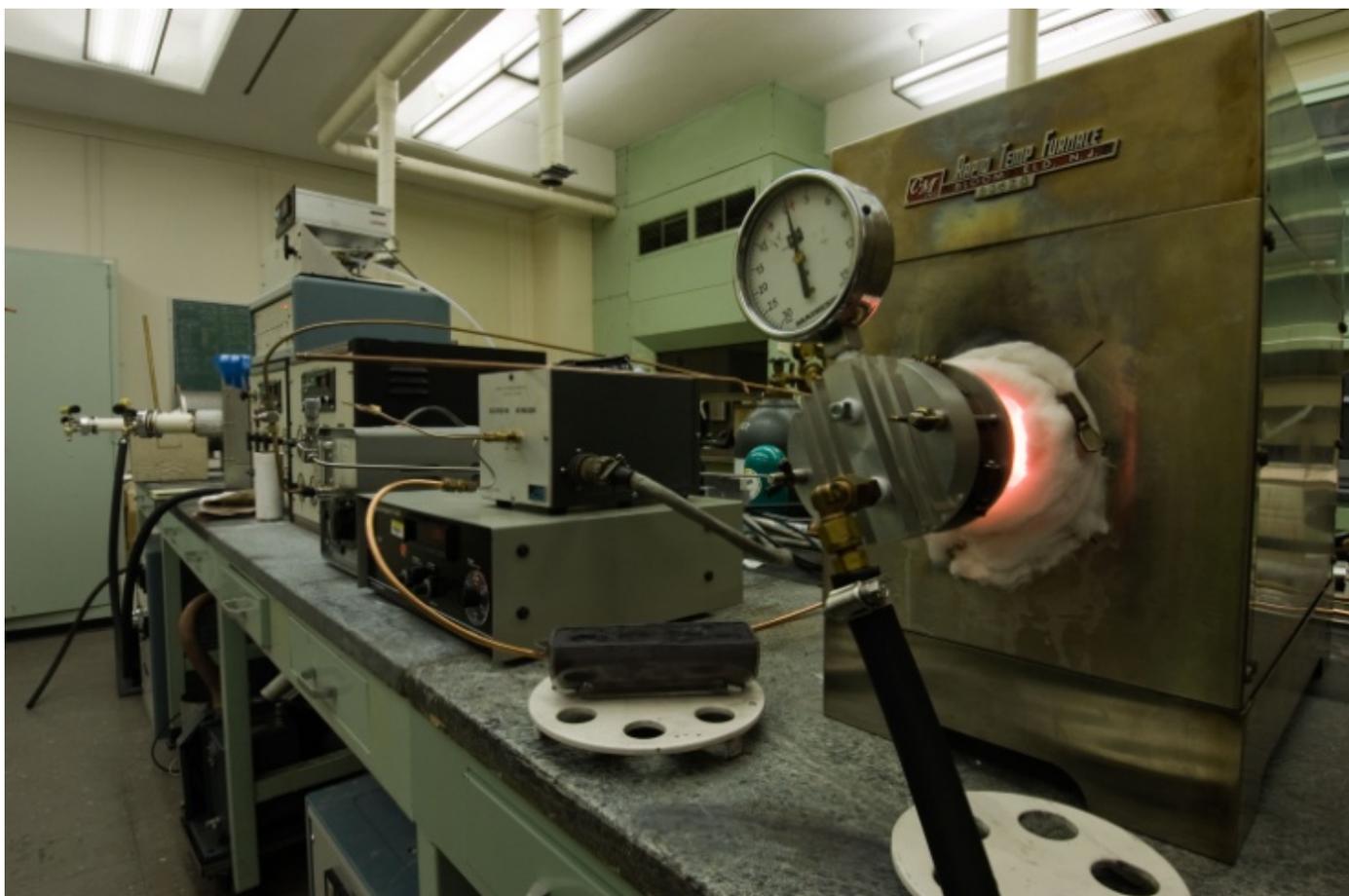
Size distribution via laser scattering

Surface area via BET adsorption, krypton



Image of Equipment Used for Annealing of Silicon in ultra-low P_{O_2} Ar

Silicon oxide surface layer reduced to elemental silicon





Primary Extinction

Dynamical scattering theory

Reduction in intensity due to destructive interference of standing waves

Zachariasen: $R = Q f(A)$

R diffraction intensity
Q intensity per unit volume
f(A) diffraction geometry

$$A = \frac{e^2 \lambda F t}{m c^2 V}$$

λ wavelength
F structure factor
T nominal crystal/domain dimension
V unit cell volume

Neutron Time-of-Flight: refine extinction parameter via Sabine model (1985)

High-energy X-ray diffraction: no extinction???



Data Collection

Neutron Time-of-Flight

SEPD, IPNS

Exposed for 2 h at 13 μ A and 30Hz, d-space range: 0.05 nm to 0.39 nm

25 keV X-ray

32 IDB, APS, eight detector machine, 0.8 mm spun kapton capillary

6° to 51° 2 Θ , 0.0005° sw, 1 s ct, d-space range: 0.058 nm to 0.474 nm

67 keV X-ray

X17B1, NSLS, focusing optics, 1.0 mm spun glass capillary

2.7° to 12° 2 Θ , 0.001° sw, 1 s ct, d-space range: 0.0890 nm to 0.393 nm

8 keV Laboratory X-ray

Siemens D500, Ge focusing IBM, sample spinner & PSD

20° to 154° 2 Θ , 0.75° /min, d-space range: 0.079 nm to 0.44 nm



Data Analysis: Rietveld code GSAS

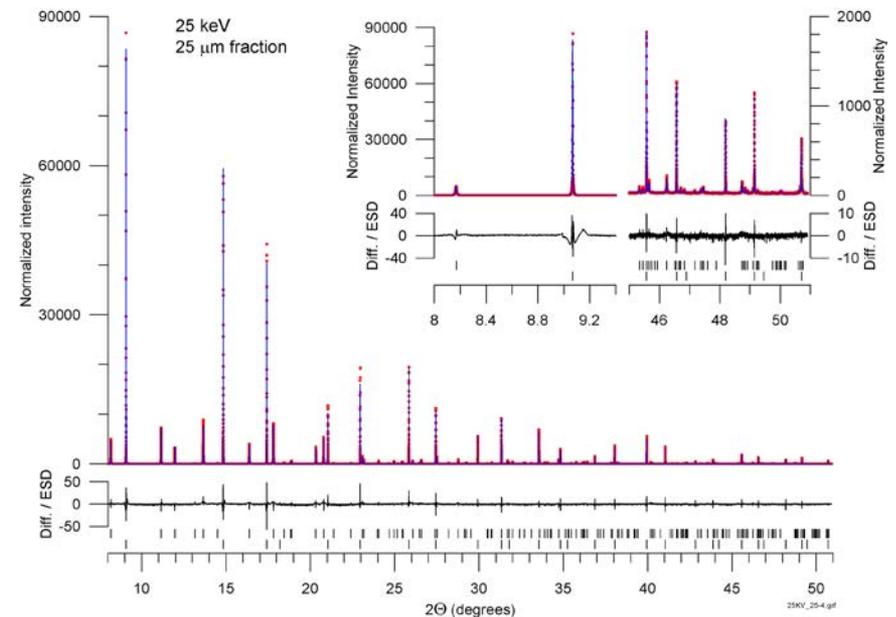
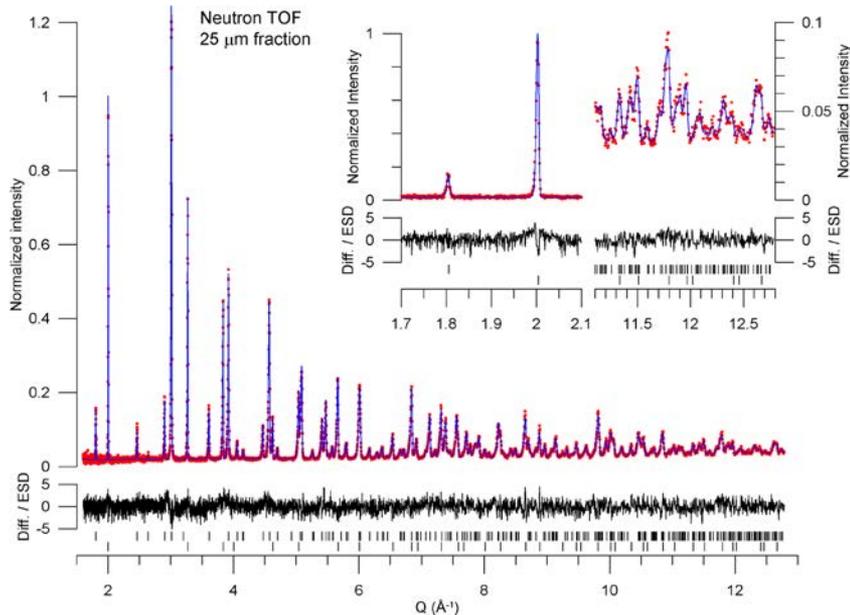
Minimize number of refined parameters

Four joint refinements

Constrain structural parameters across 24 specimens

Microstructural parameters constrained for alumina

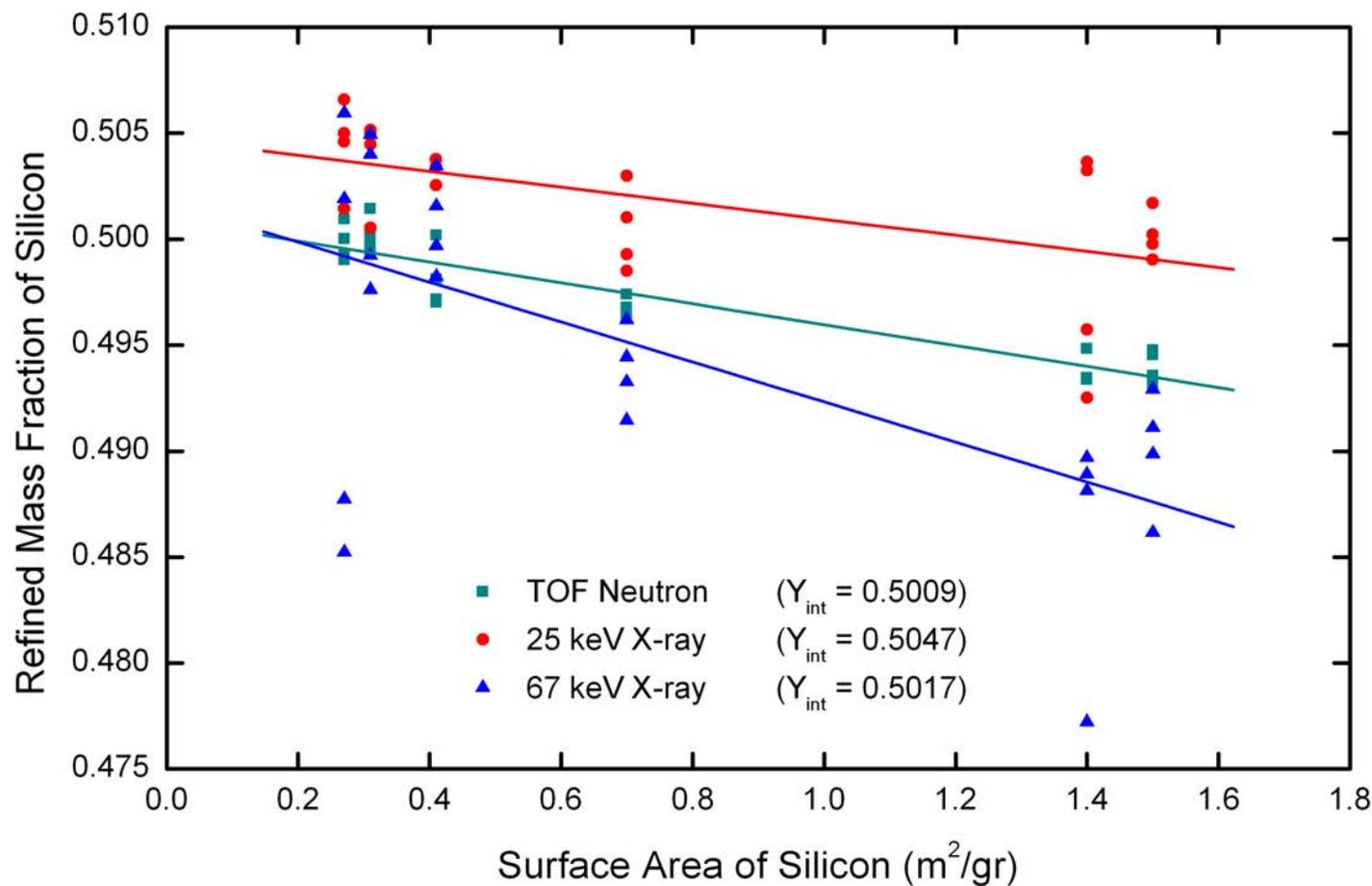
Microstructural & extinction parameters constrained within each lot of silicon





SRM 676a Certification Data

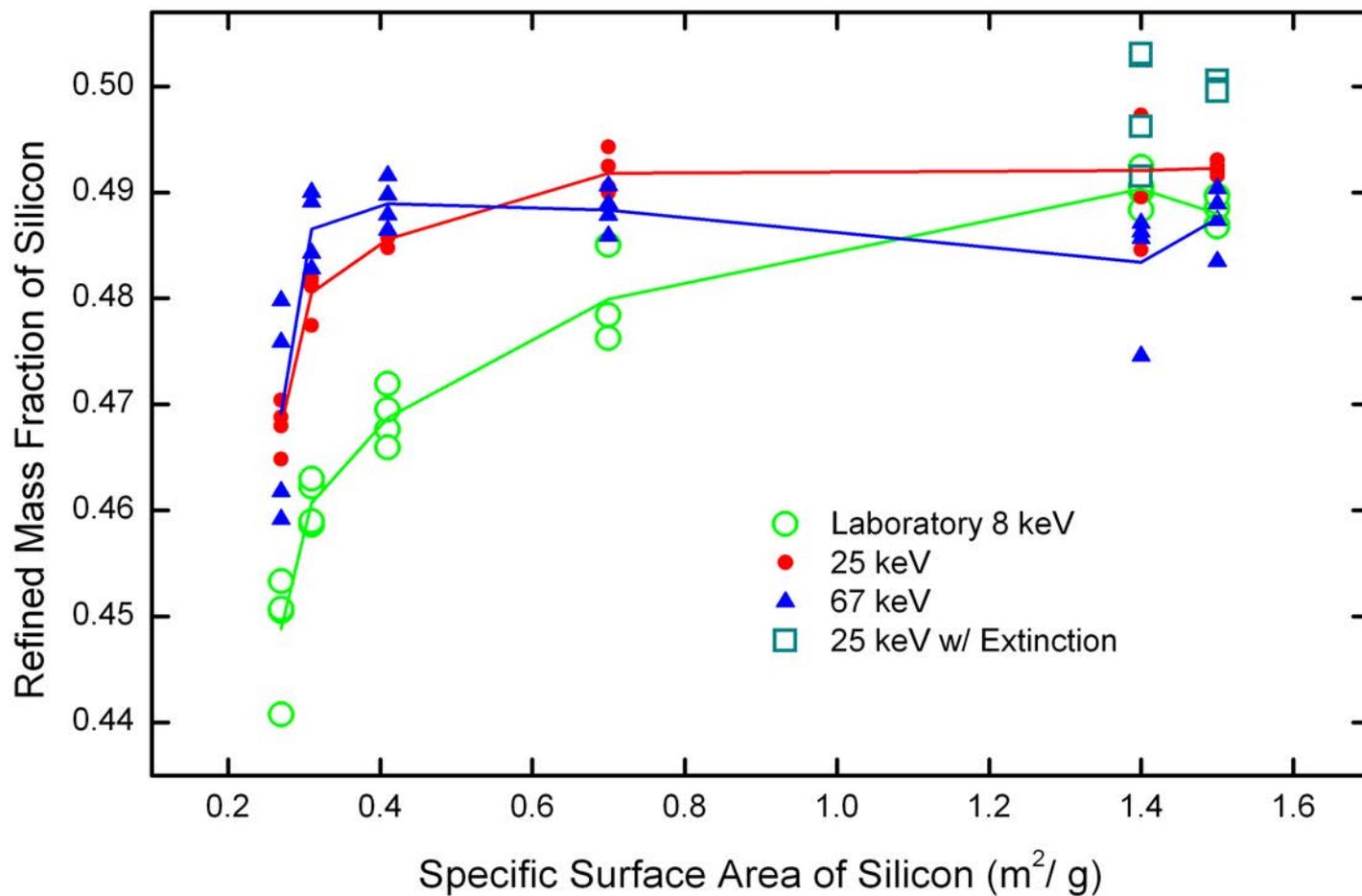
SRM 676a 99.02% \pm 1.11% phase pure alumina





X-ray Data With / Without Extinction Correction

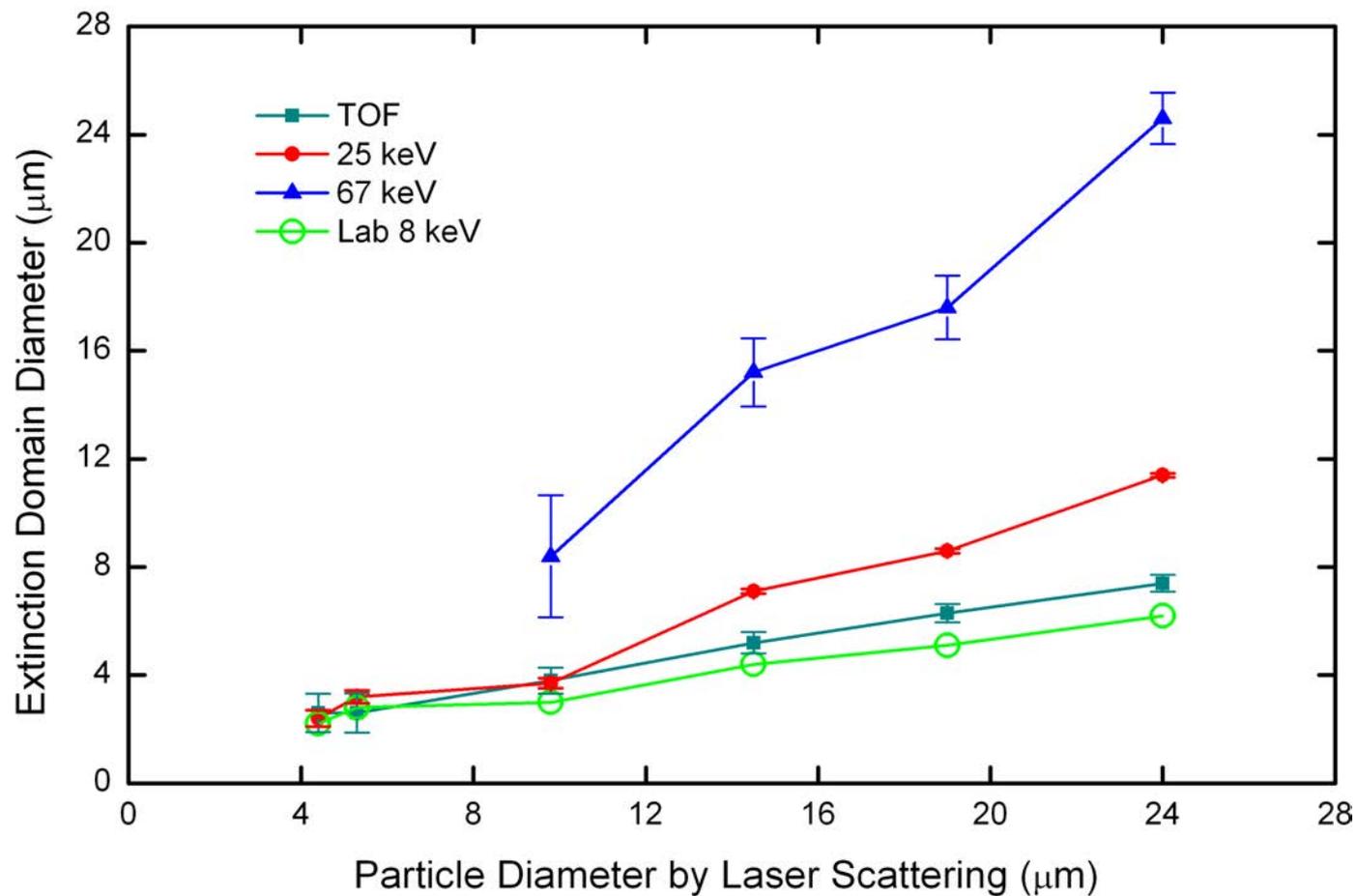
Extinction effects illustrated at < 5 μm particle size range & 67 keV





Refined Extinction Domain Sizes

Consistent within each method
Inconsistent between methods





Thickness of Oxide (Gunk) Layer on Silicon Powder

Computed from line slope of certification data

$$\begin{aligned}\text{Slope} &= \Delta \text{ mass of Si displaced by SiO}_2 / \Delta \text{ surface area of Si} \\ &= 0.0061 \text{ g/m}^2 \text{ (average slope of TOF, 25 \& 67 keV data sets)}\end{aligned}$$

$$\text{Density of SiO}_2 = 2.2 \text{ g/cm}^3 = 0.45 \text{ cm}^3/\text{g}$$

$$\begin{aligned}\text{Layer thickness} &= 0.0061 \text{ (g/m}^2) * 0.45 \text{ (cm}^3/\text{g)} * 10^{-6} \text{ (cm}^3/\text{m}^3) \\ &= 0.0028 \text{ (cm}^3/\text{m}^2) * 10^{-6} \text{ (cm}^3/\text{m}^3)\end{aligned}$$

$$\text{Layer thickness} = 2.8 * 10^{-9} \text{ m} = 2.8 \text{ nm}$$

Generally accepted value for thickness of self-limiting oxide layer on silicon under ambient conditions is 1.5 nm



Conclusions

The divergent beam diffractometer has yielded lattice parameter values that are credible to ± 8 femtometers

We look forward to results from the parallel beam diffractometer

The *Fundamental Parameters Approach* yields the best fits to the observations and plausible refined parameters describing the experimental configuration

NIST quantitative analysis SRM 676a certified for amorphous content

SRM 676a now permits measurement of layer thickness or amorphous content in unknowns

Extinction affects diffraction intensity measurements with both small domain sizes and high energy radiation